

Spin transport in a semiconductor channel

Condensed Matter Seminar, Korea University

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March 9, 2015

우수한 전문 인력

- 국내 최대의 스핀트로닉스 전문 연구조직
- 20여 년간 자성 관련 기술 연구로 풍부한 경험을 보유

탁월한 연구성과

- 스핀 제어 소자 분야의 NSC급 논문 등 질적 양적 성과 창출
- 차세대 스핀소자 분야의 다수의 핵심 특허 보유

우수한 연구 인프라

- Cluster MBE를 비롯한 스핀소재/소자용 전용 장비보유
- KIST Micro/Nano FAB과 직접 연계한 인프라 시스템 구축



**12 regular researchers,
25 postdocs & students**

Science
Control of Spin Precession in a Spin-Injected Field Effect Transistor
Hyun Cheol Koo, *et al.*
Science 325, 1515 (2008)
DOI: 10.1126/science.1173987

Control of Spin Precession in a Spin-Injected Field Effect Transistor

LETTERS
Interdimensional universality of dynamic interfaces

nature materials ARTICLES
PUBLISHED ONLINE 13 DECEMBER 2009 | DOI: 10.1038/NMAT2608

Oscillatory spin-polarized tunnelling from silicon quantum wells controlled by electric field

LETTER
doi:10.1038/nature08187

Magnetic-field-controlled reconfigurable semiconductor logic

LETTERS **nature nanotechnology**
PUBLISHED ONLINE 25 MAY 2010 | DOI: 10.1038/NNANO.2010.107

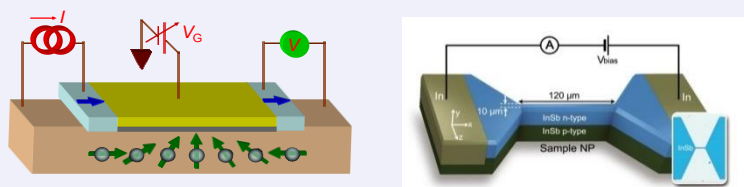
Electrical detection of coherent spin precession using the ballistic intrinsic spin Hall effect

Won Young Choi^{1,2}, Hyung-jun Kim¹, Joonyeon Chang¹, Suk Hee Han¹, Hyun Cheol Koo^{2*} and Mark Johnson²



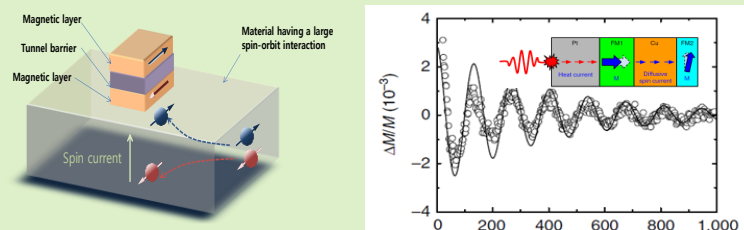
Research Fields

Spin Transistor and logic device



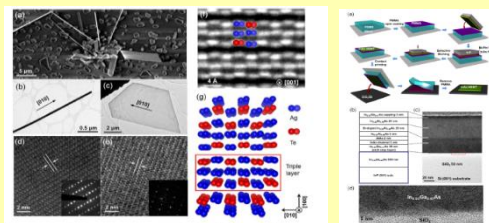
Science (2009), Nature (2013),
Nature Nanotech. (2015)

Spin torque memory



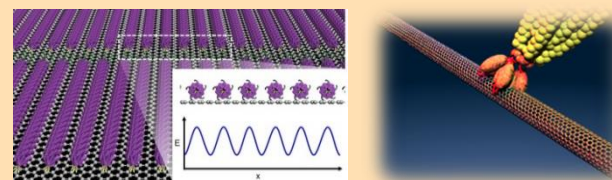
Nature (2009), Nature Comm. (2014), Nature
Physics (2015), Nano Letters (2016)

New materials for spintronics



Nano Letters (2011, 2012), ACS Nano (2013),

Bio-electronic material



Advanced Materials (2015, 2016)

Experimental Facilities

Cluster MBE system



Clean room facilities (495 m², 69 equipments)



E-beam lithography system



Physical Property Measurement System

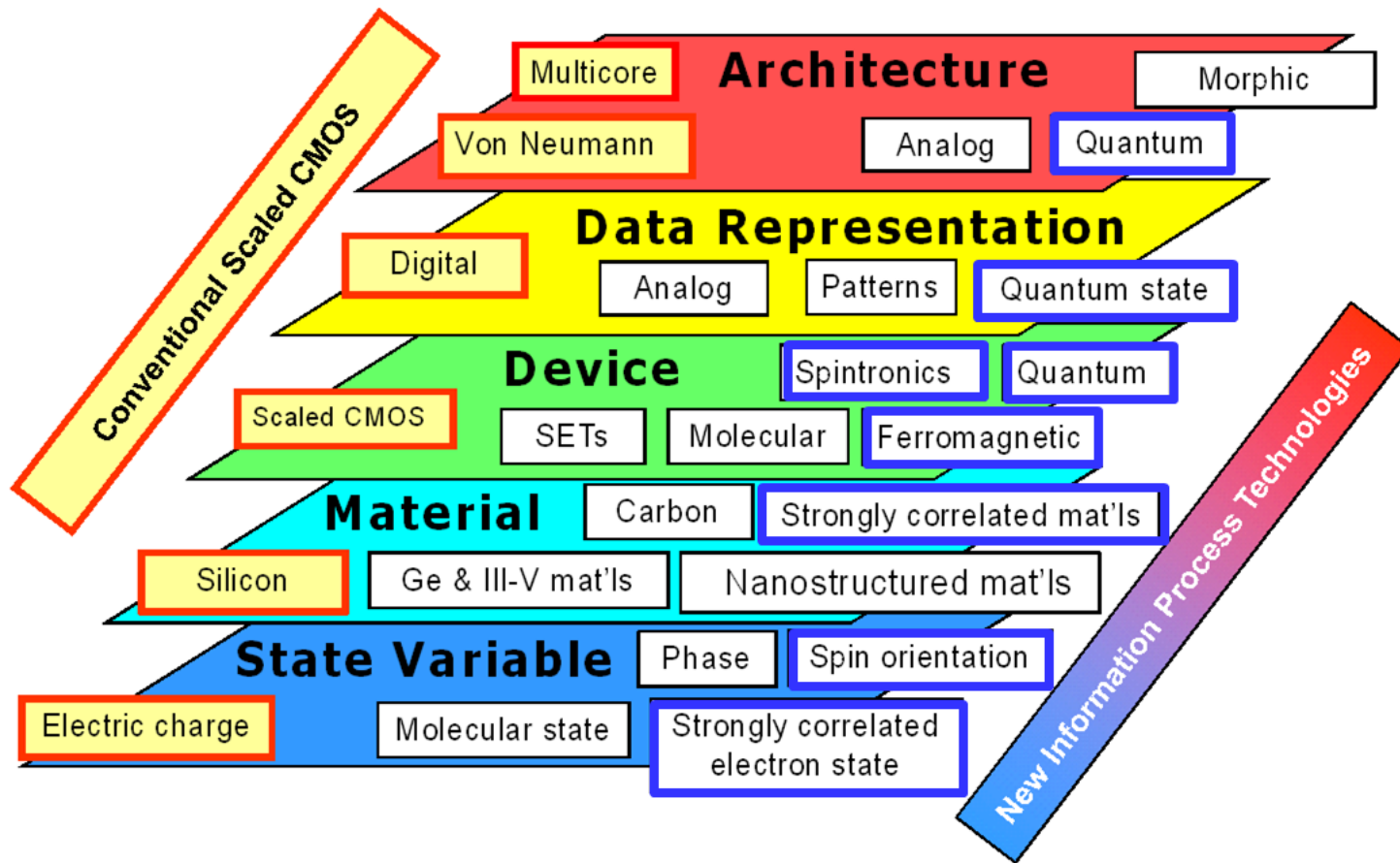


Ion Beam /Plasma Etcher



Why spintronics?

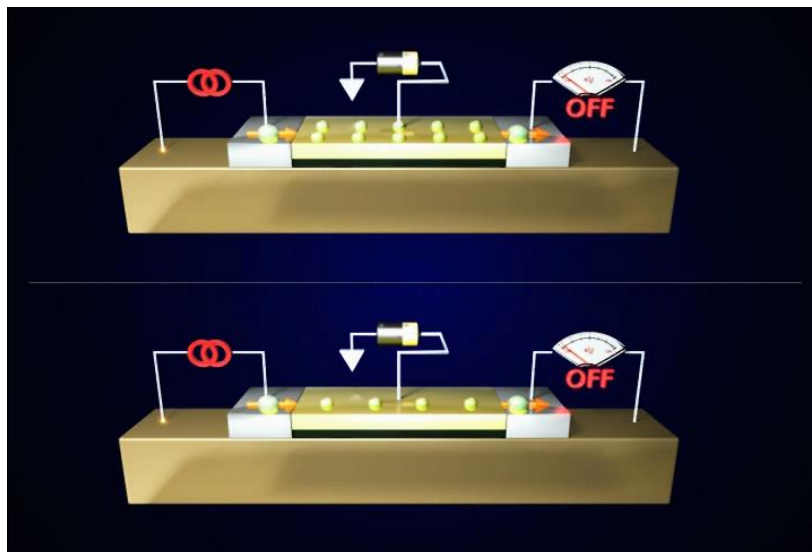
International Technology Roadmap for Semiconductors (2013)



Spintronics-related field

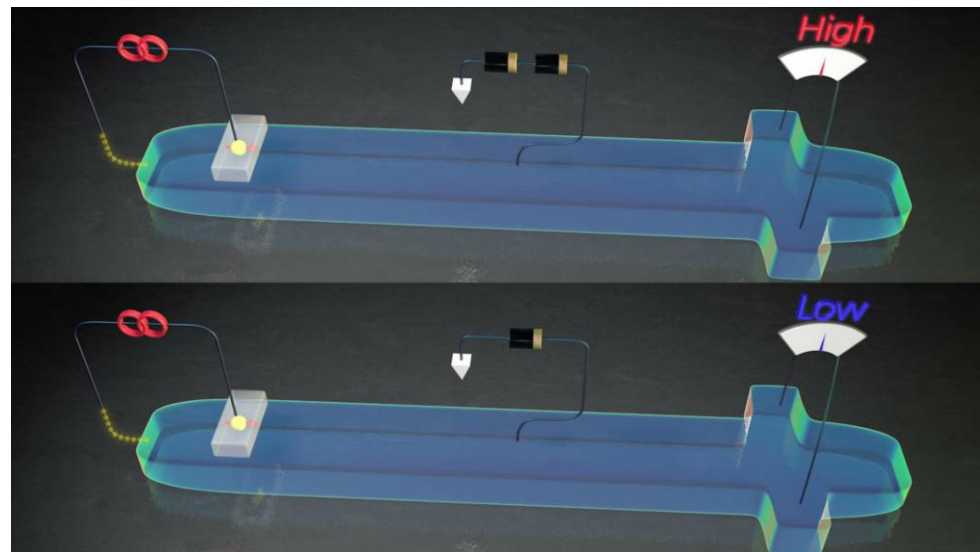
Two fascinating devices in semiconductor spintronics

Spin-FET



(Science 2009)

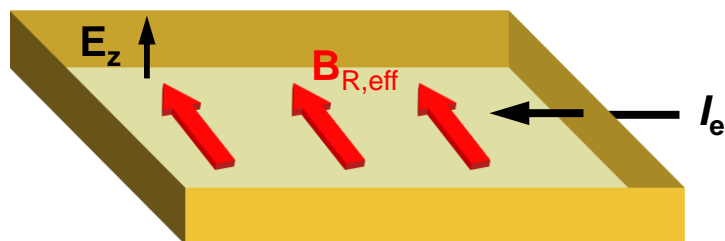
Spin Hall Transistor



(Nature Nanotechnology 2015)

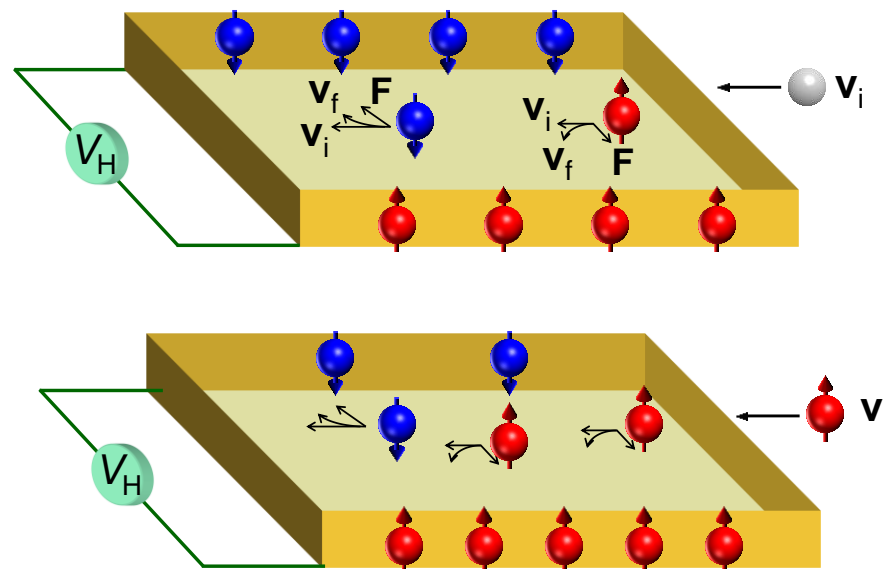
Main Physics

Rashba effect: When the perpendicular electric field exists, the flow of electrons induces the effective magnetic field.



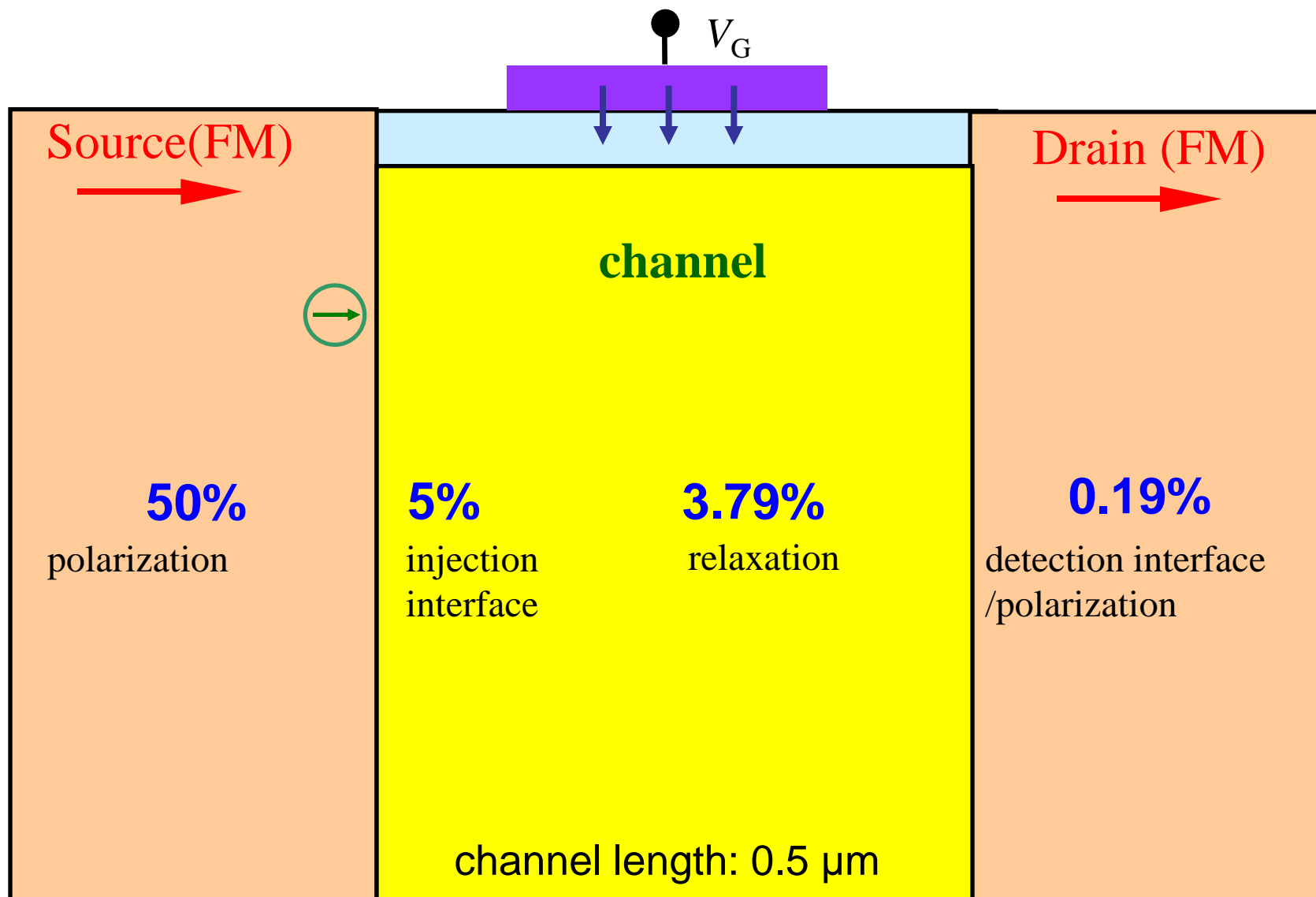
→ Gate control of spin orientation

Spin Hall effect: The direction of the carrier deviation depends on the spin orientation.



→ Realization of spin-charge conversion

Difficulties for developing spin transistor



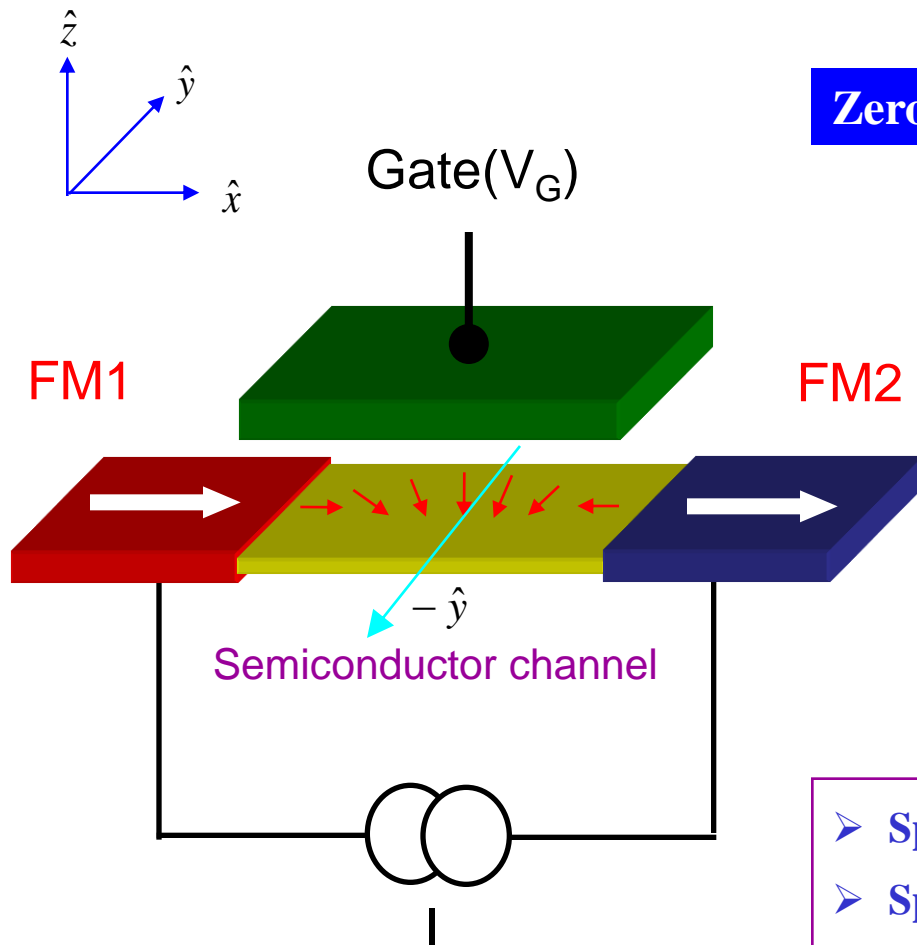
Spin transport channel

Spin field effect transistor (spin-FET)

Datta and Das, APL 1990

Zero-field spin splitting (Rashba Hamiltonian)

$$H_R = \alpha (\vec{\sigma} \times \vec{k}) \cdot \hat{z}$$



Spin precession angle for the electron traveling the channel length L

$$\Delta\theta = \frac{2m\alpha L}{\hbar^2}$$

- Spin injection from FM1
- Spin precession by Rashba spin-orbit interaction.
- Spin detection at FM2 after $\Delta\theta$ – precession

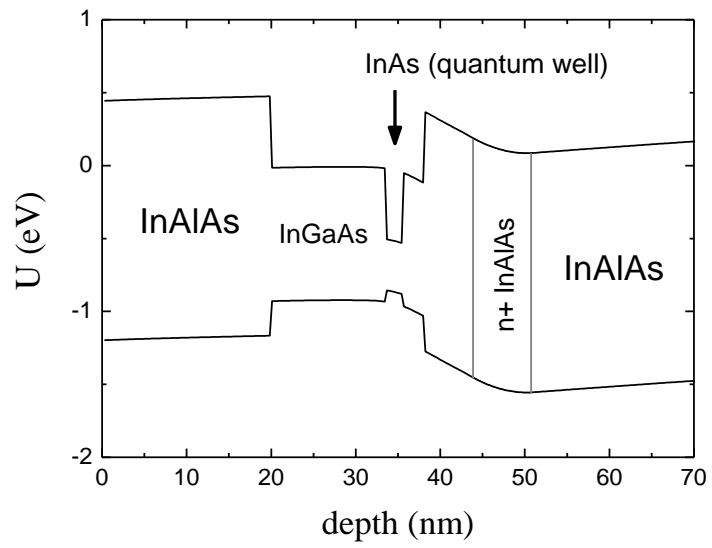
Material : InAs quantum well structure

InAs (2 nm)
In _{0.52} Al _{0.48} As (20 nm)
In _{0.53} Ga _{0.47} As (13.5 nm)
InAs quantum well (2 nm)
In _{0.53} Ga _{0.47} As (2.5 nm)
In _{0.52} Al _{0.48} As (6 nm)
n+ In _{0.52} Al _{0.48} As (7 nm) , n = 4 × 10 ¹⁸ /cm ³
In _{0.52} Al _{0.48} As (buffer)
Semi-insulated InP(100)

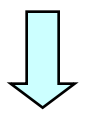
Temperature (K)	Carrier Density (× 10 ¹² cm ⁻²)	Mobility (cm ² /Vsec)	Sheet resistance (Ω)
300	~2	~10000	~250
1.8	~2	~60000	~45

Large spin-orbit interaction parameter : $\alpha \approx 1.0 \times 10^{-11}$ eVm ($T = 1.8$ K)¹

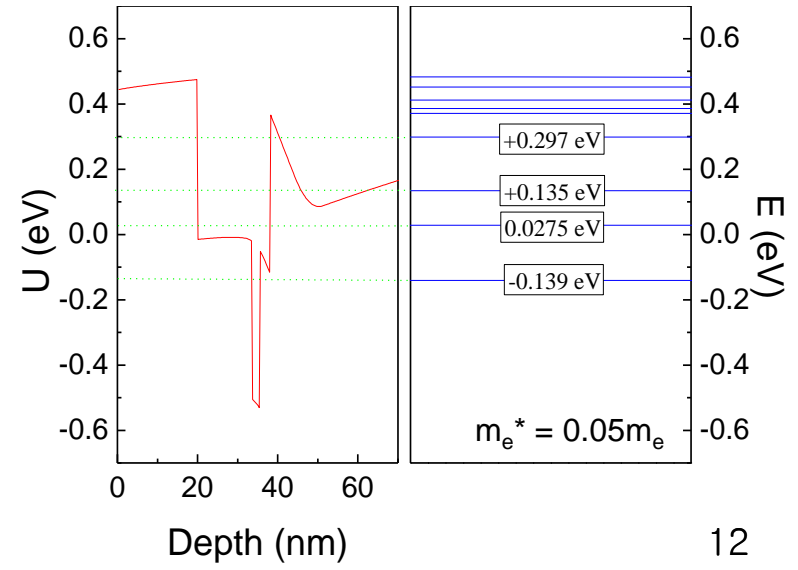
InAs (2nm)
In _{0.52} Al _{0.48} As (20 nm)
In _{0.53} Ga _{0.47} As (13.5 nm)
InAs QW (2nm)
In _{0.53} Ga _{0.47} As (2.5 nm)
In _{0.52} Al _{0.48} As (6 nm)
n+ In _{0.52} Al _{0.48} As (7 nm)
In _{0.52} Al _{0.48} As (300 nm)
InP substrate



Only one quantum level exists below the Fermi energy.

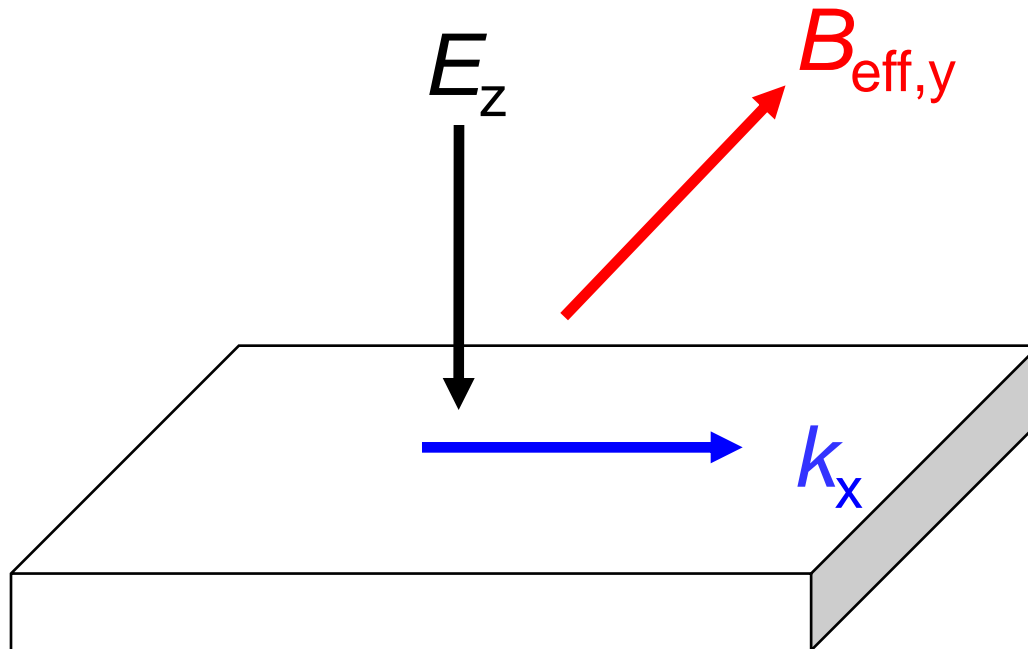


No magneto-intersubband scattering

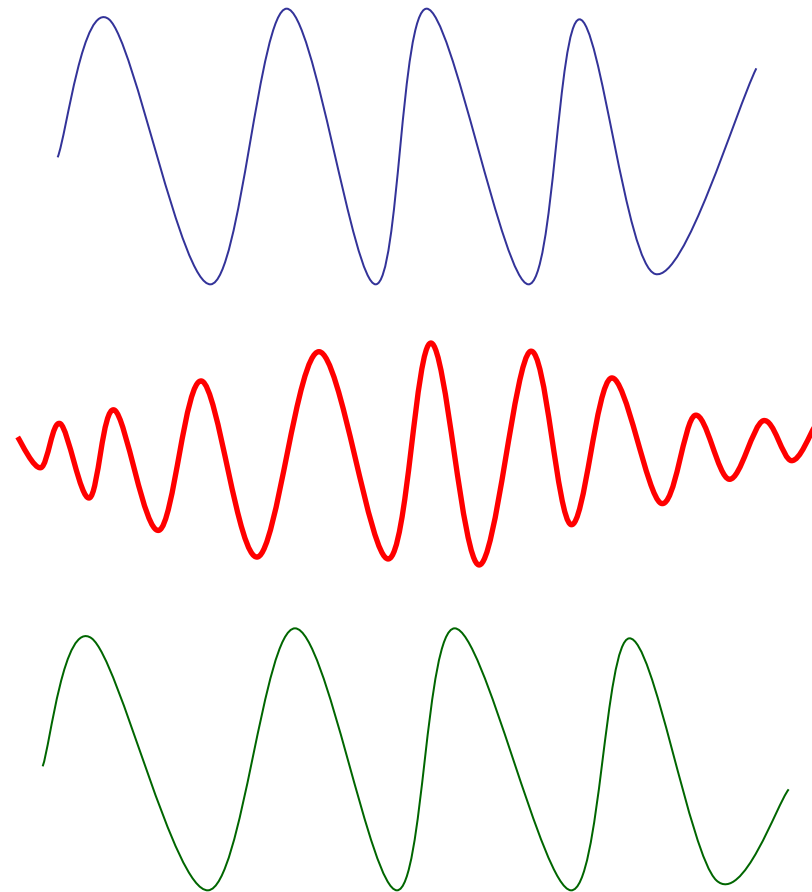
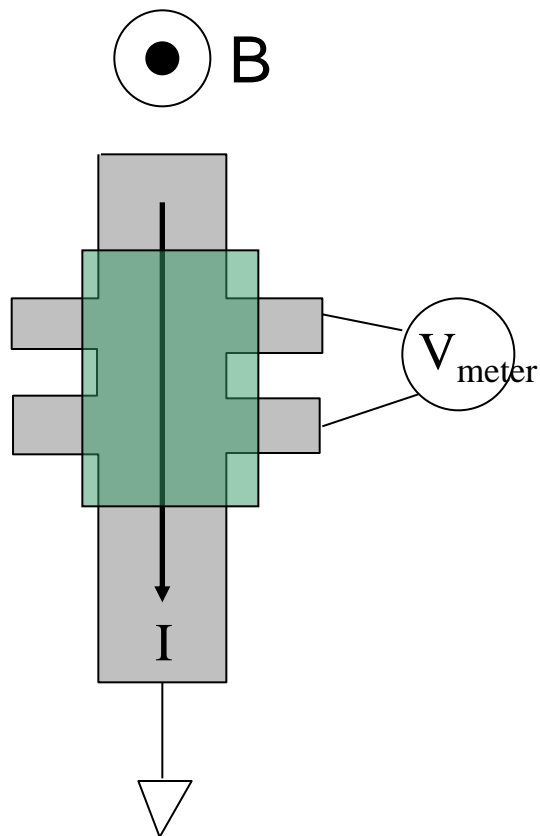


Spin-orbit interaction (Rashba effect)

- When the perpendicular electric field (E_z) exists, the flow of electrons (k_x) in two-dimensional electron gas (2-DEG) produces unbalanced population of spin up and down electrons due to the effective magnetic field (B_y) induced by so-called Rashba effect.



Shubnikov-de Haas (SdH) Oscillation



Shubnikov-de Haas oscillation

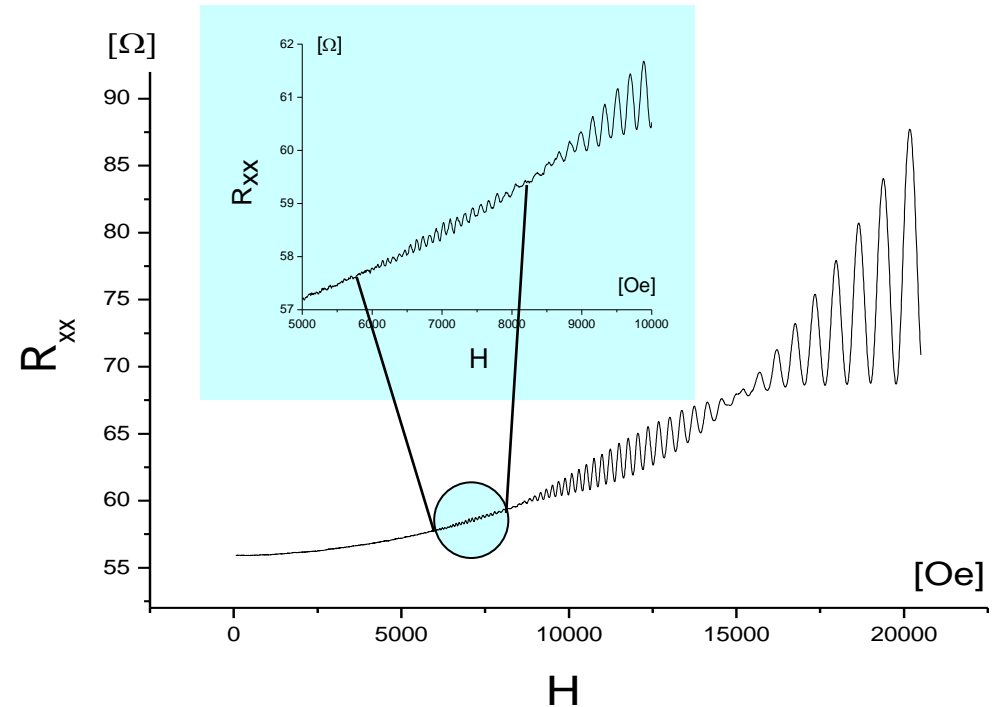
$$\Delta\left(\frac{1}{B}\right) = \frac{2e}{h} \frac{1}{n_{2D}}$$

$$n_{2D} = n_{\uparrow} + n_{\downarrow}$$

Zero-field spin splitting

➔ Beating pattern in R_{xx}

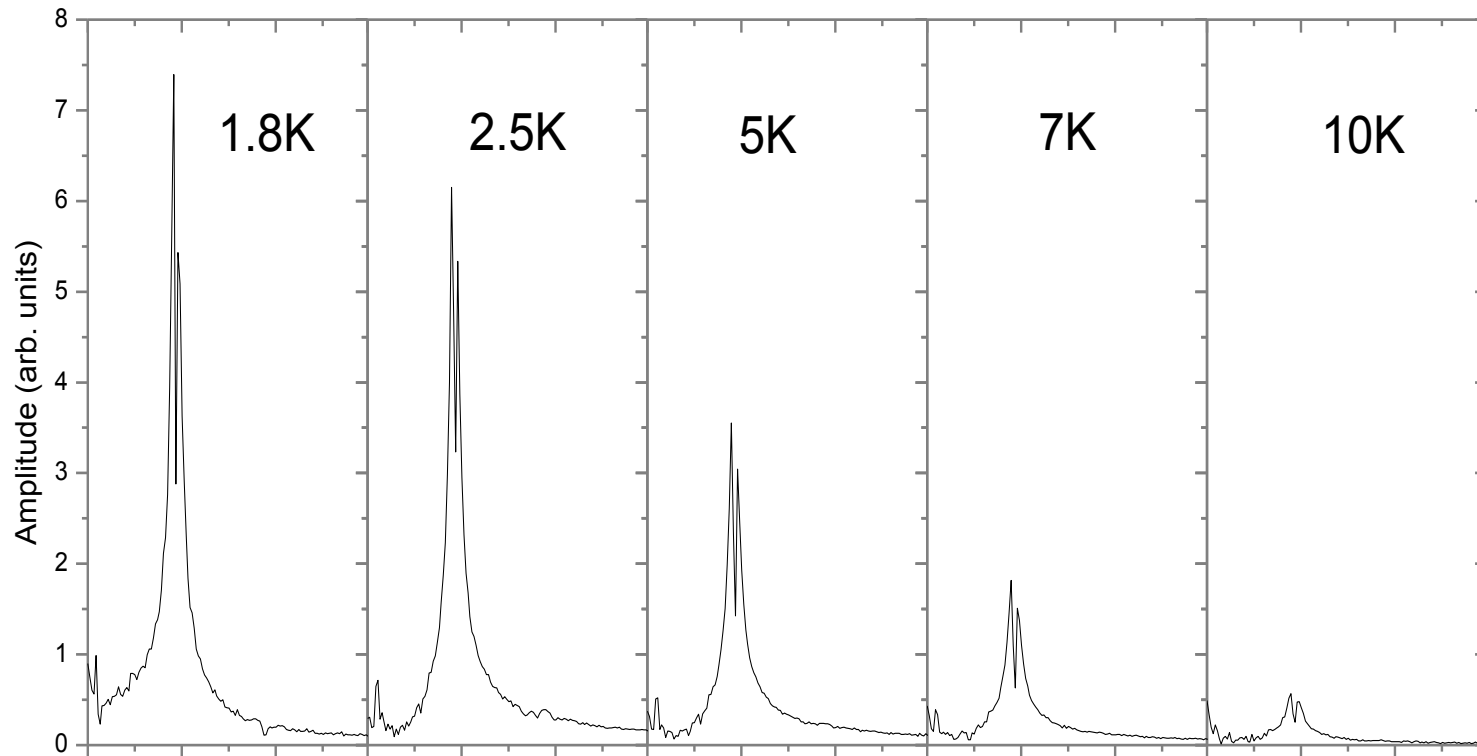
$$n_{\uparrow} - n_{\downarrow} = \frac{e}{h} \frac{1}{\Delta(1/B)_{beat}}$$



$$\Delta E = \frac{\pi \hbar^2}{m^*} (n_{\uparrow} - n_{\downarrow})$$

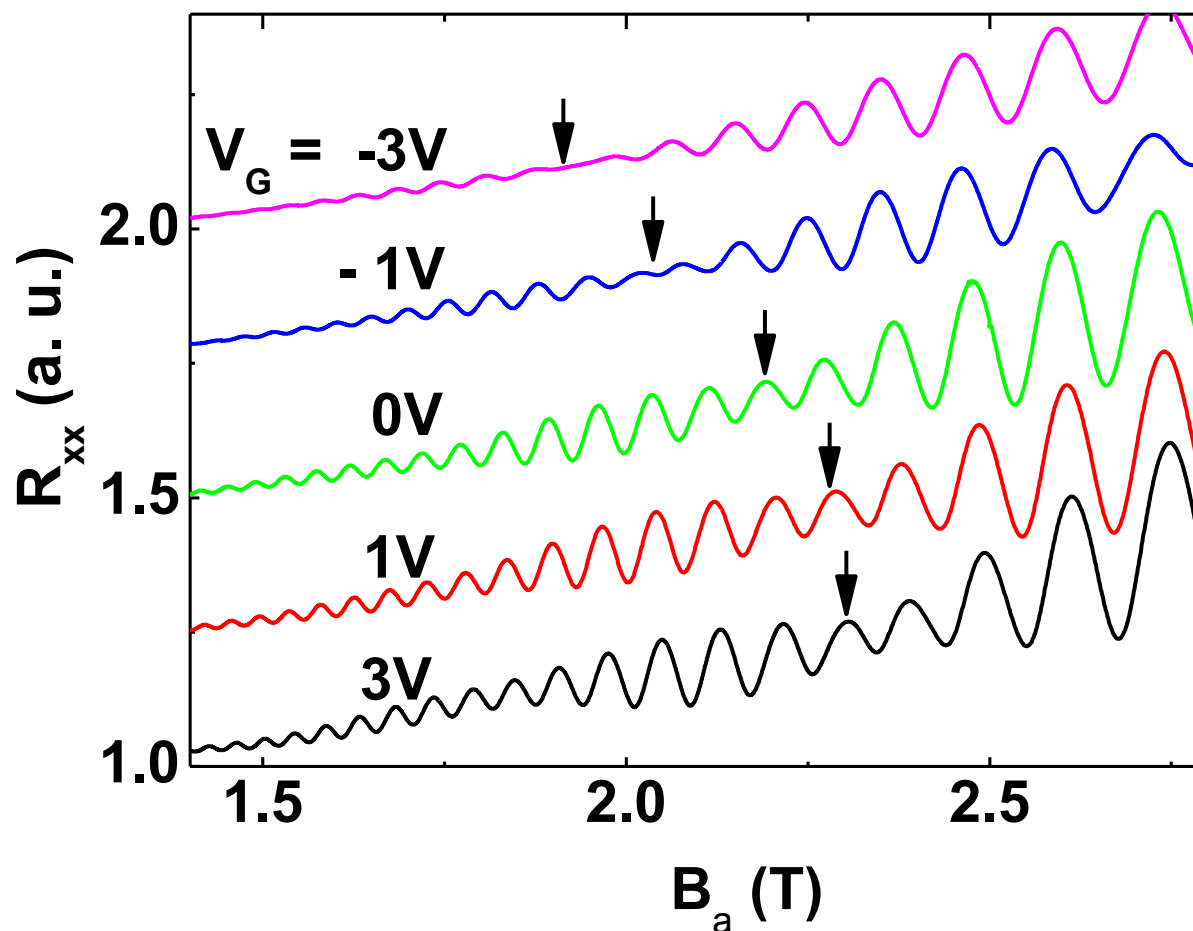
Using the observed ΔE , $\alpha = \Delta E / (2k_F) = \Delta E / (2\pi n_{2D})^{0.5}$

Temperature dependence of SdH measurement

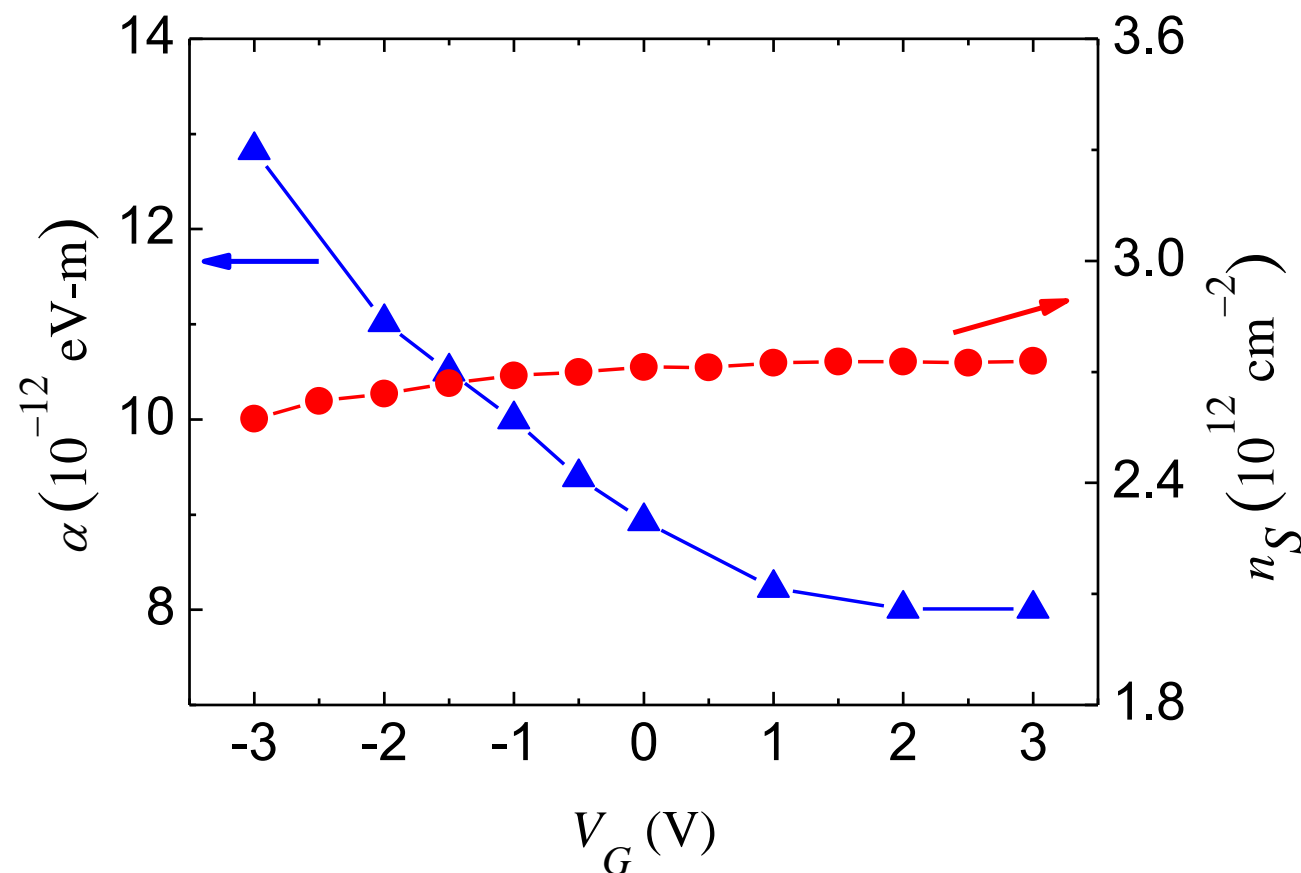


Major two peaks are not intermixing term between 1st
and 2nd sub-band.

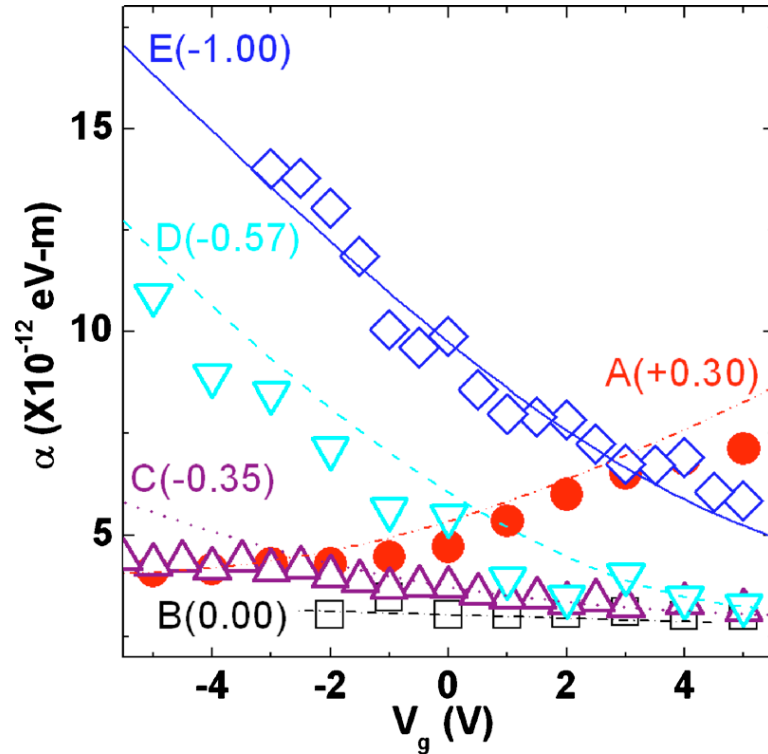
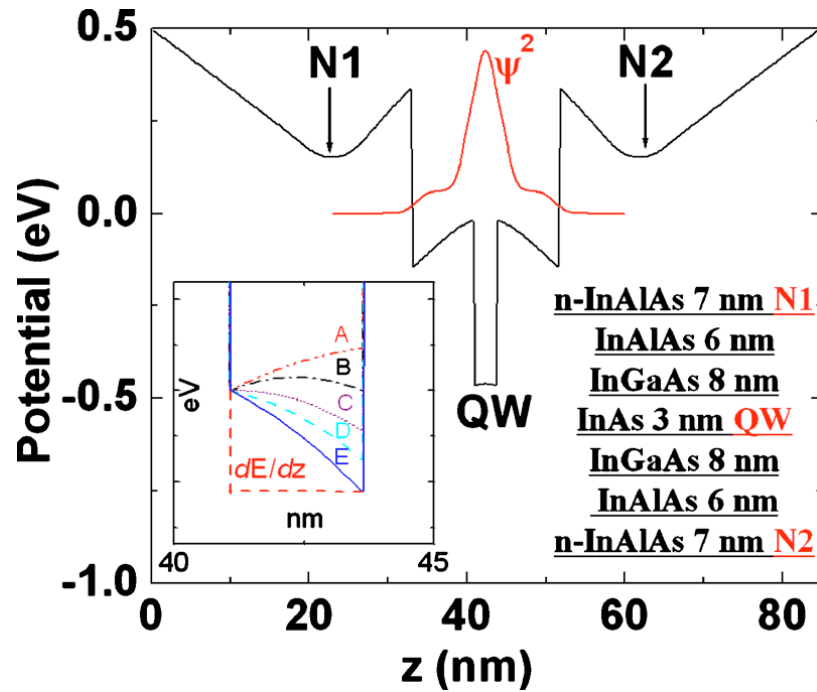
Gate voltage dependence of SdH oscillations



Gate voltage dependence of α and carrier density

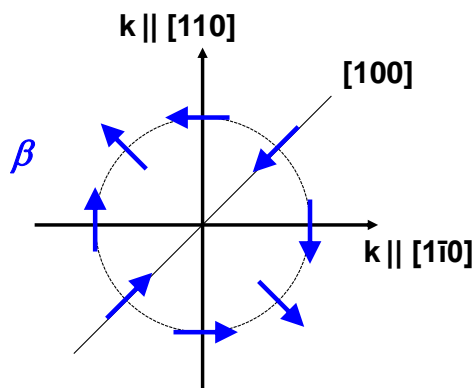
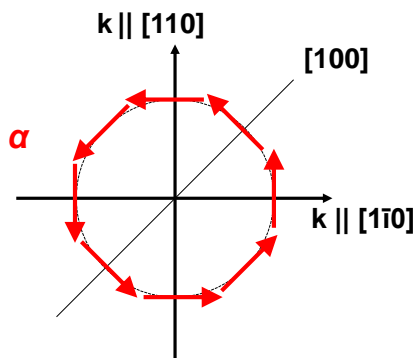


Rashba constant control using doping levels

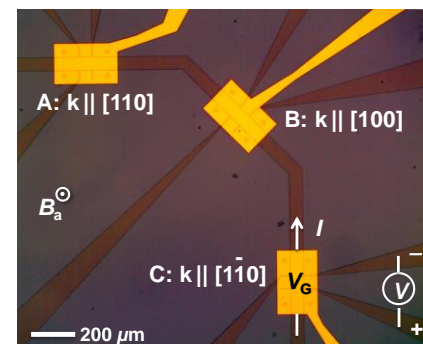
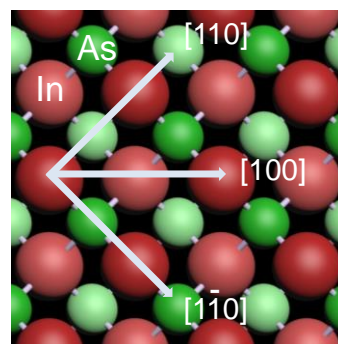
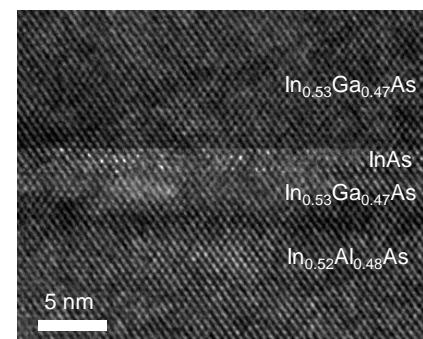


K.-H. Kim *et al.* *Appl. Phys. Lett.* 97,012504 (2010)

Crystal direction dependence of Rashba (α) and Dresselhaus (β) effects

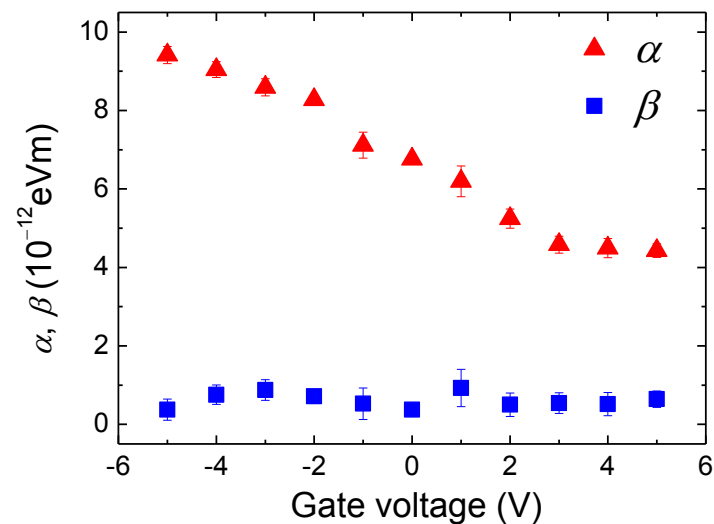
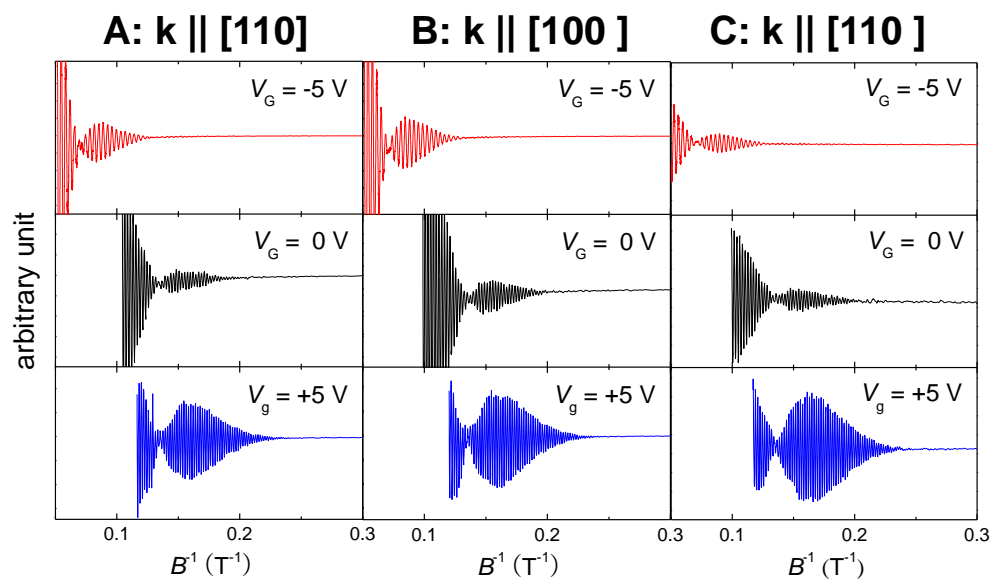


InAs 2 nm
In _{0.52} Al _{0.48} As 20 nm
In _{0.53} Ga _{0.47} As 13.5 nm
InAs (Quantum Well) 2 nm
In _{0.53} Ga _{0.47} As 2.5 nm
In _{0.52} Al _{0.48} As 6 nm
n+ In _{0.52} Al _{0.48} As 7 nm ($n = 4 \times 10^{18}$)
In _{0.52} Al _{0.48} As 300nm
Semi-insulating InP(001) sub



Y. H. Park *et al.* *Appl. Phys. Lett.* 103, 252407 (2013)

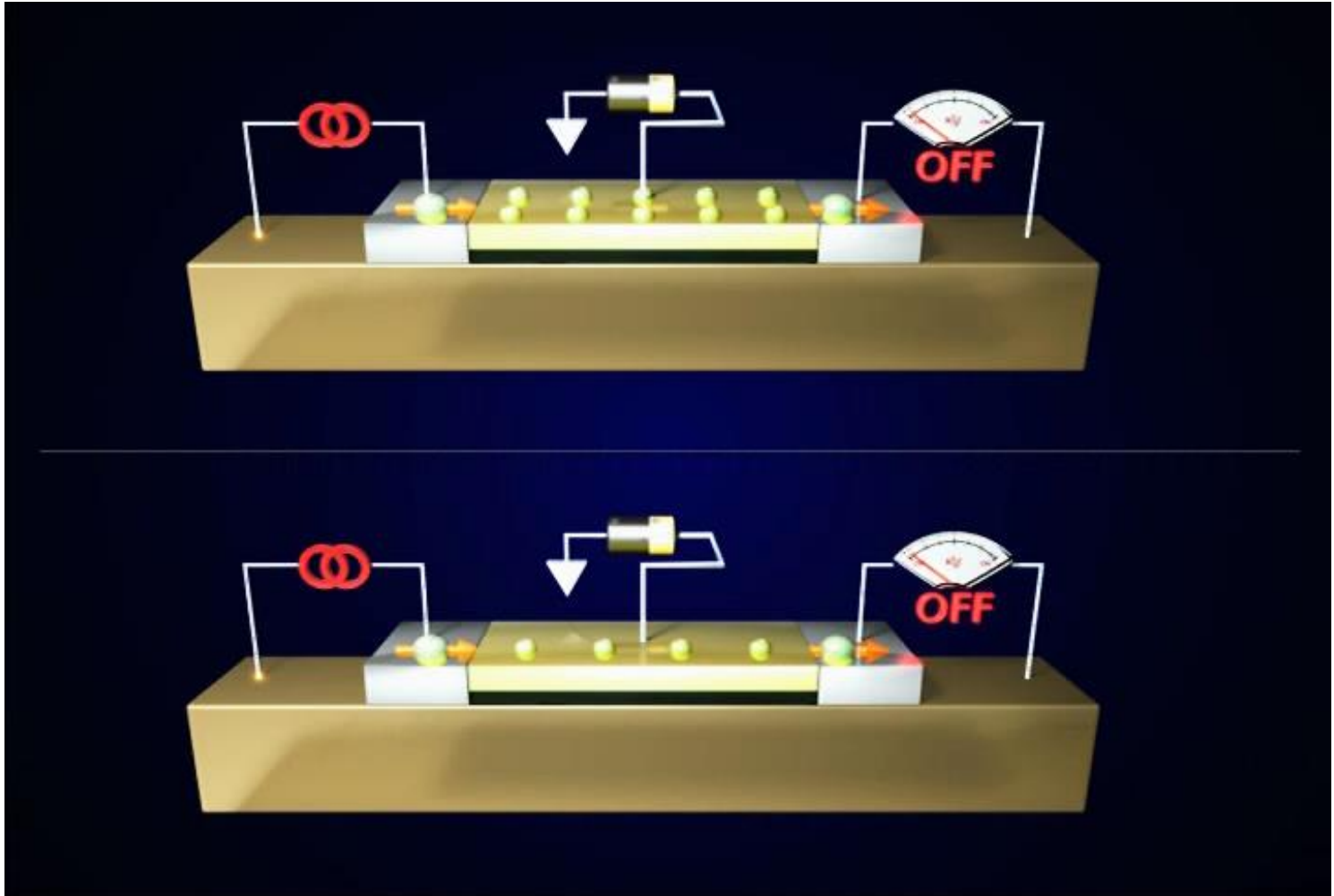
Separation of Rashba and Dresselhaus term



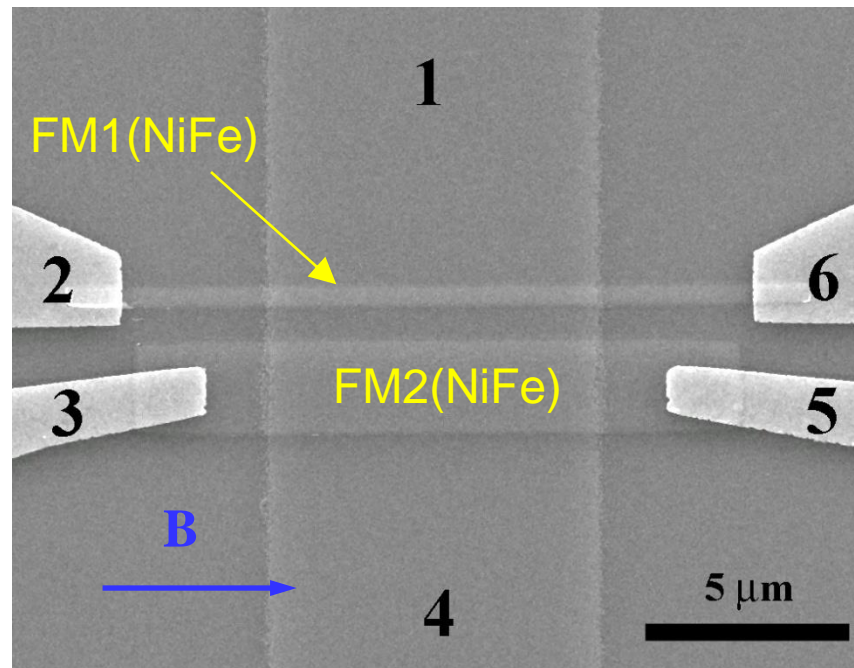
Y. H. Park *et al.* *Appl. Phys. Lett.* 103, 252407 (2013)

Spin-FET operation

Spin-FET



Semiconductor spin-valve : NiFe/(InAs-2DEG)/NiFe

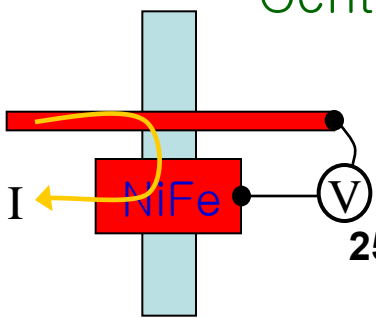


Local measurement
(Spin-valve effect)

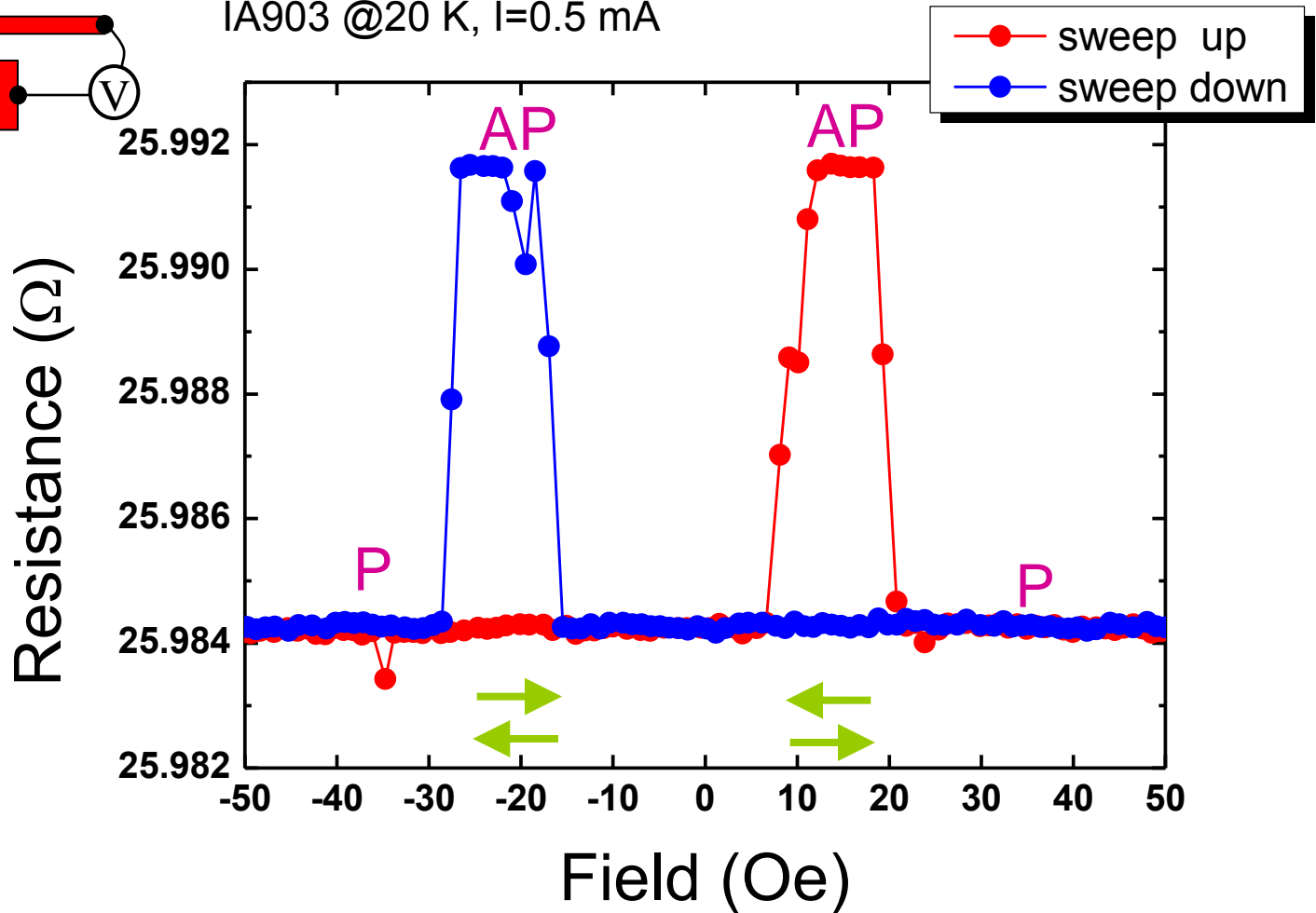
Non-local measurement
(Spin accumulation)

Local spin valve measurement at $T = 20$ K

Center-to-center distance between FM1 and FM2 = $2.2 \mu\text{m}$

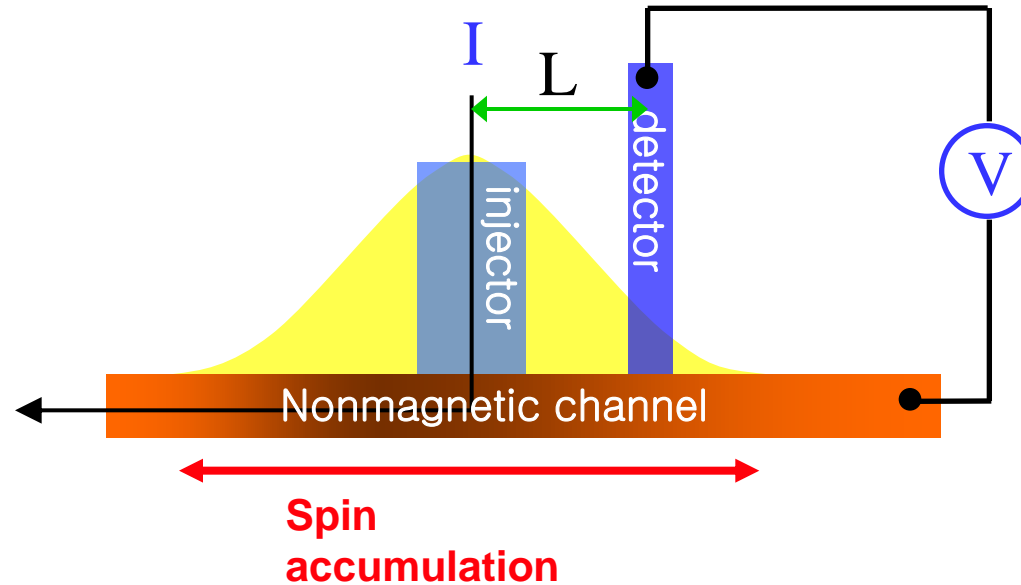


IA903 @20 K, I=0.5 mA



Non-local measurement

Ferromagnetic injector and detector



$$\frac{\mu}{I} = R_{spin} = \frac{\eta_1 \eta_2 \rho \lambda_s}{A} e^{-L/\lambda_s}$$

$$= \frac{\eta_1 \eta_2 R_t \lambda_s}{W} e^{-L/\lambda_s} \quad (\text{for 2 DEG})$$

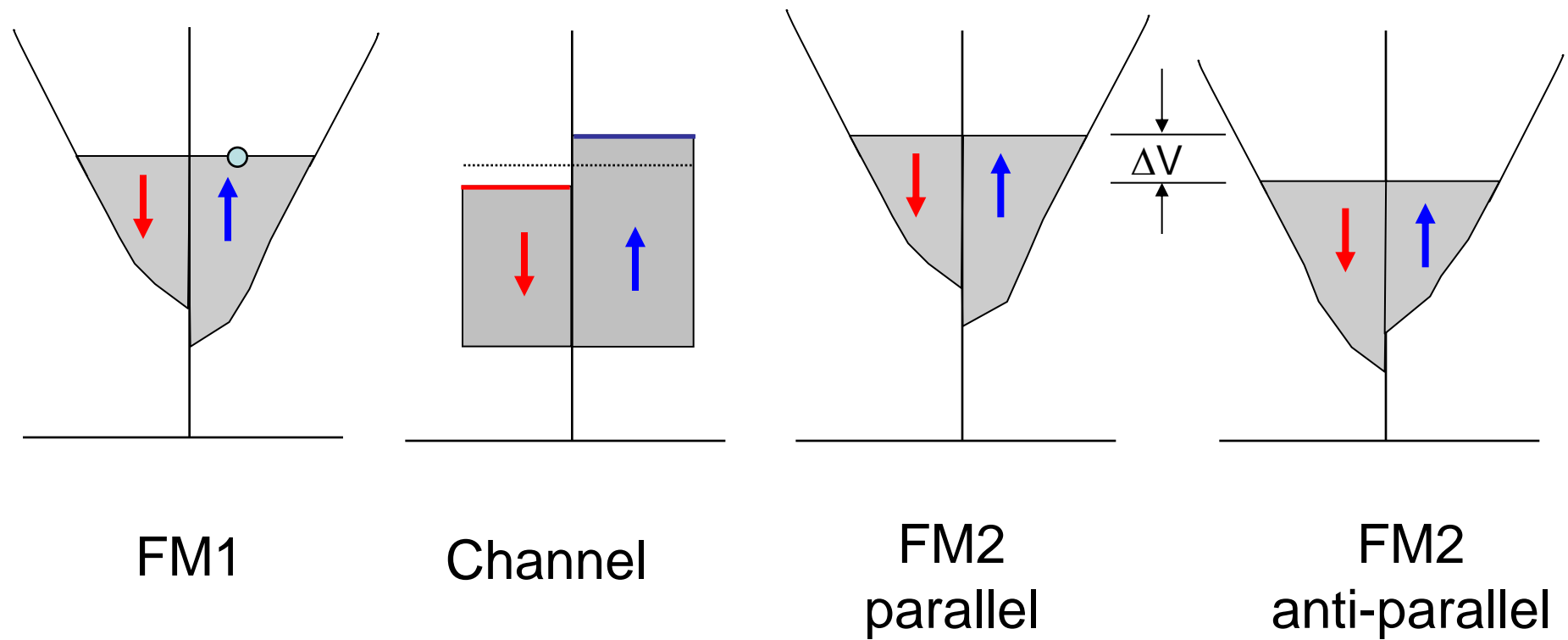
R_t : sheet resistance
 λ_s : spin diffusion length

Johnson and Silsbee, Phys. Rev. B **37**, 5312 (1988)

Johnson, J. Appl. Phys. **75**, 6714 (1994)

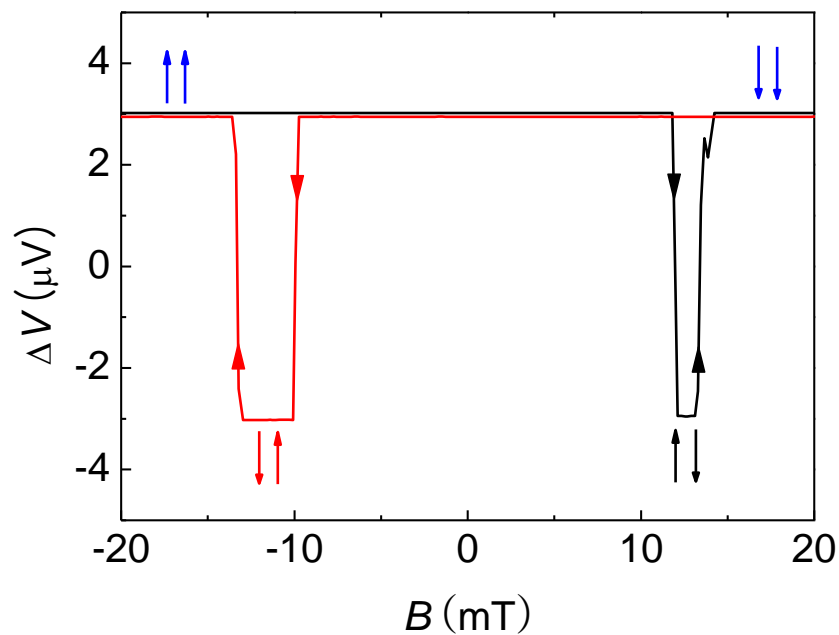
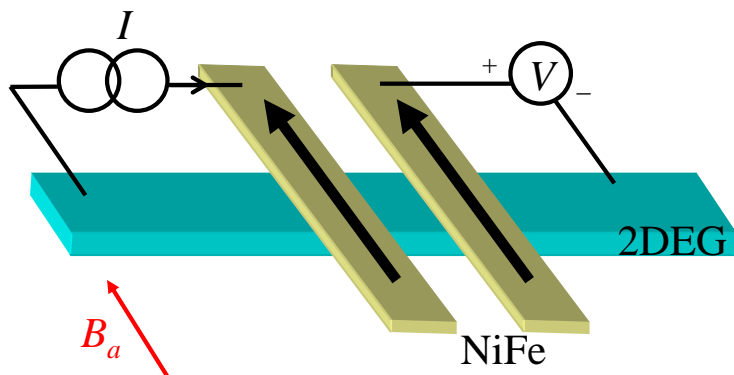
Zutic et al., Rev. Mod. Phys. **76**, 323 (2004)

Mechanism of non-local signal



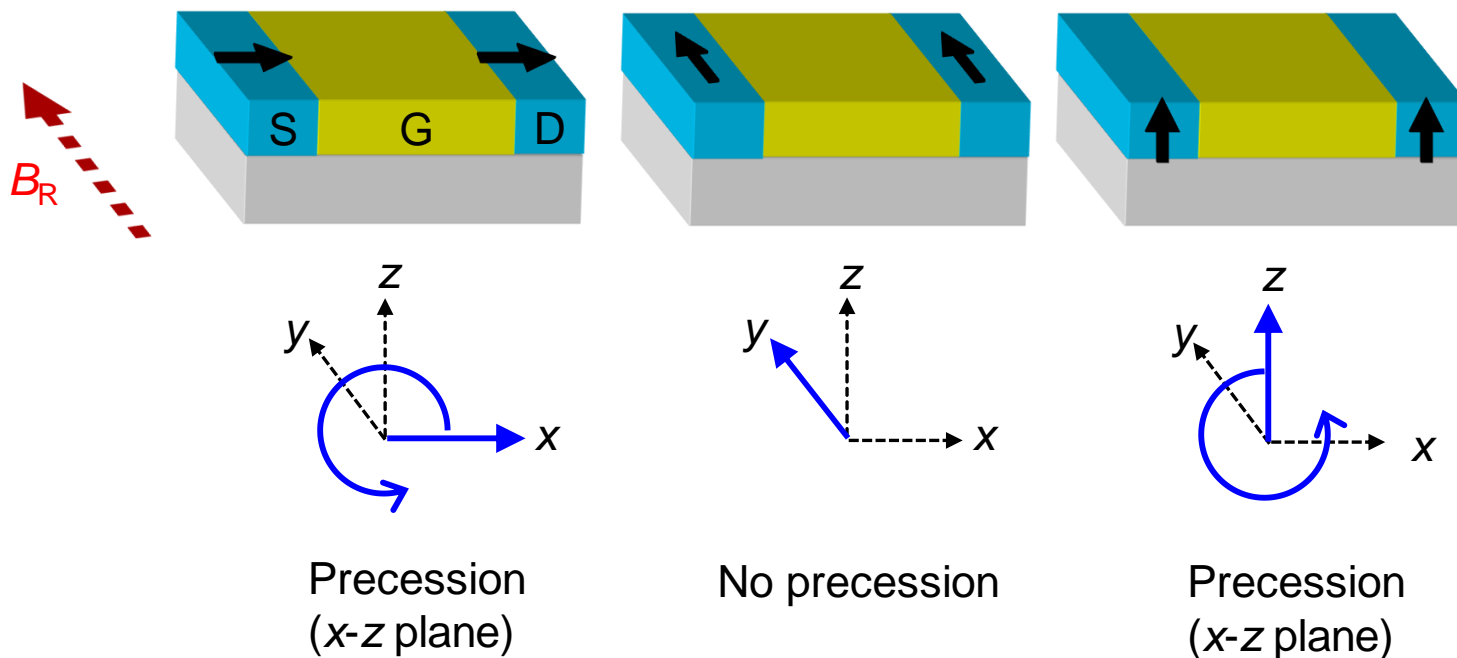
Non-local measurement of spin injection

A clear spin valve signal by non-local measurement is observed at 1.8K.



H. C. Koo *et al.* *Science* 325,1515 (2009)

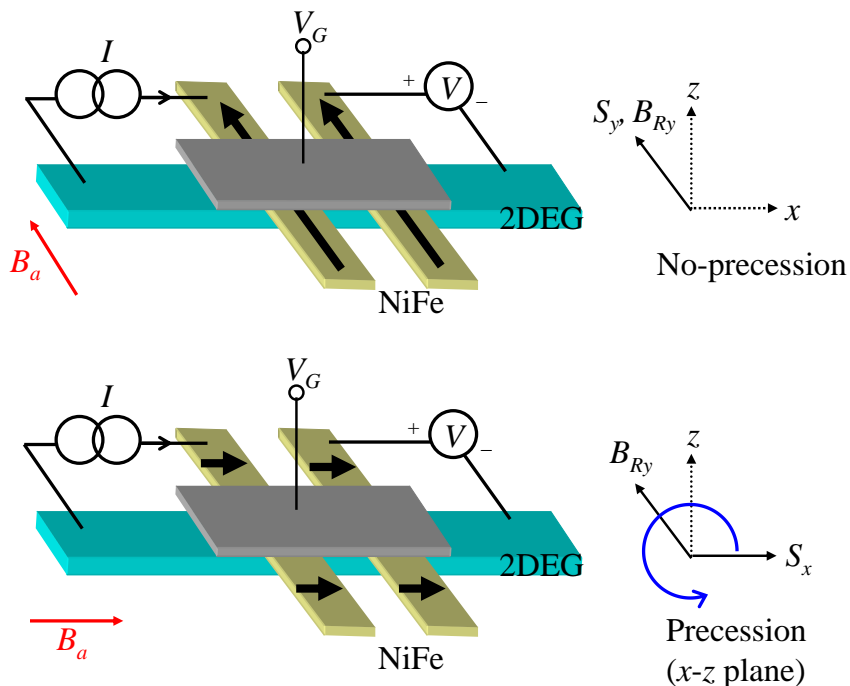
Magnetization direction dependence of spin precession



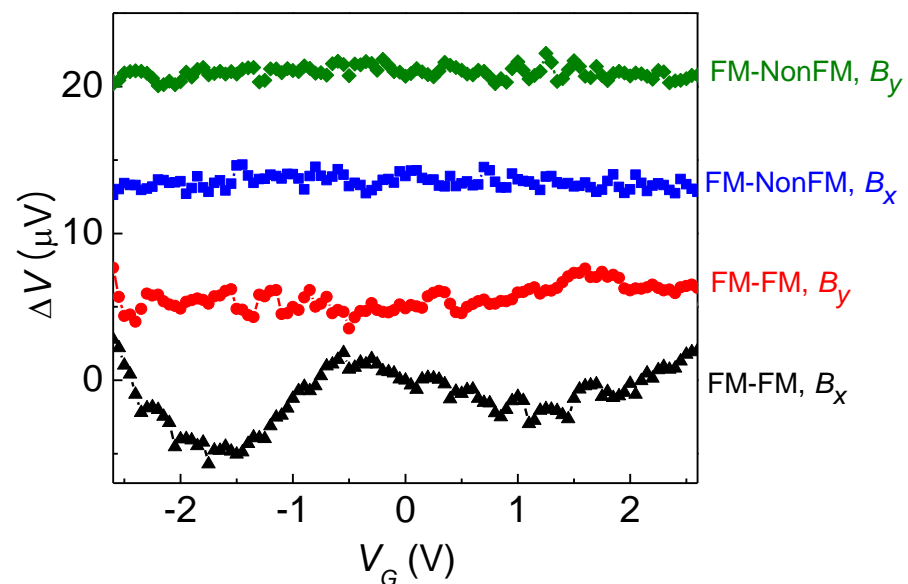
Magnetization of FM should be aligned in either x or z direction.

Gate control of spin precession

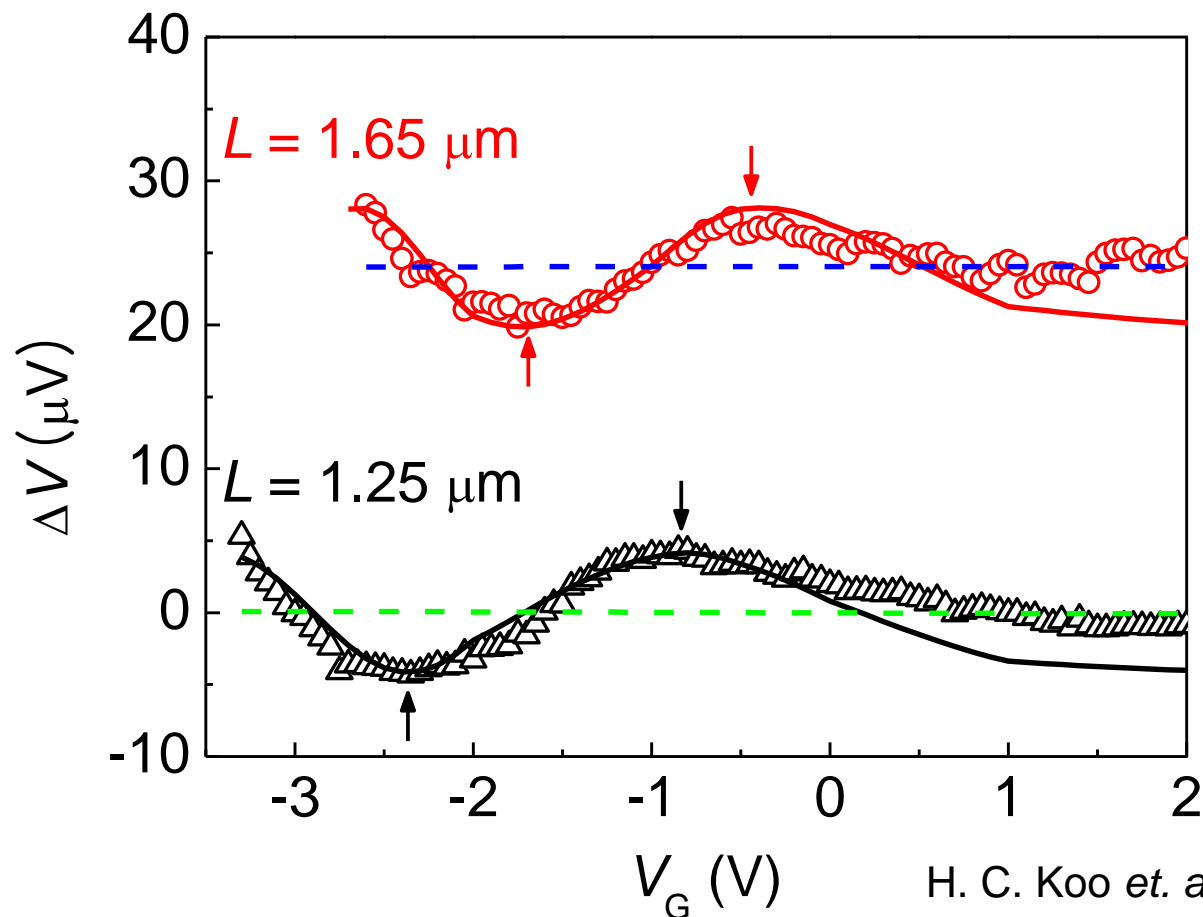
Magnetization configuration



Measurement at 1.8K



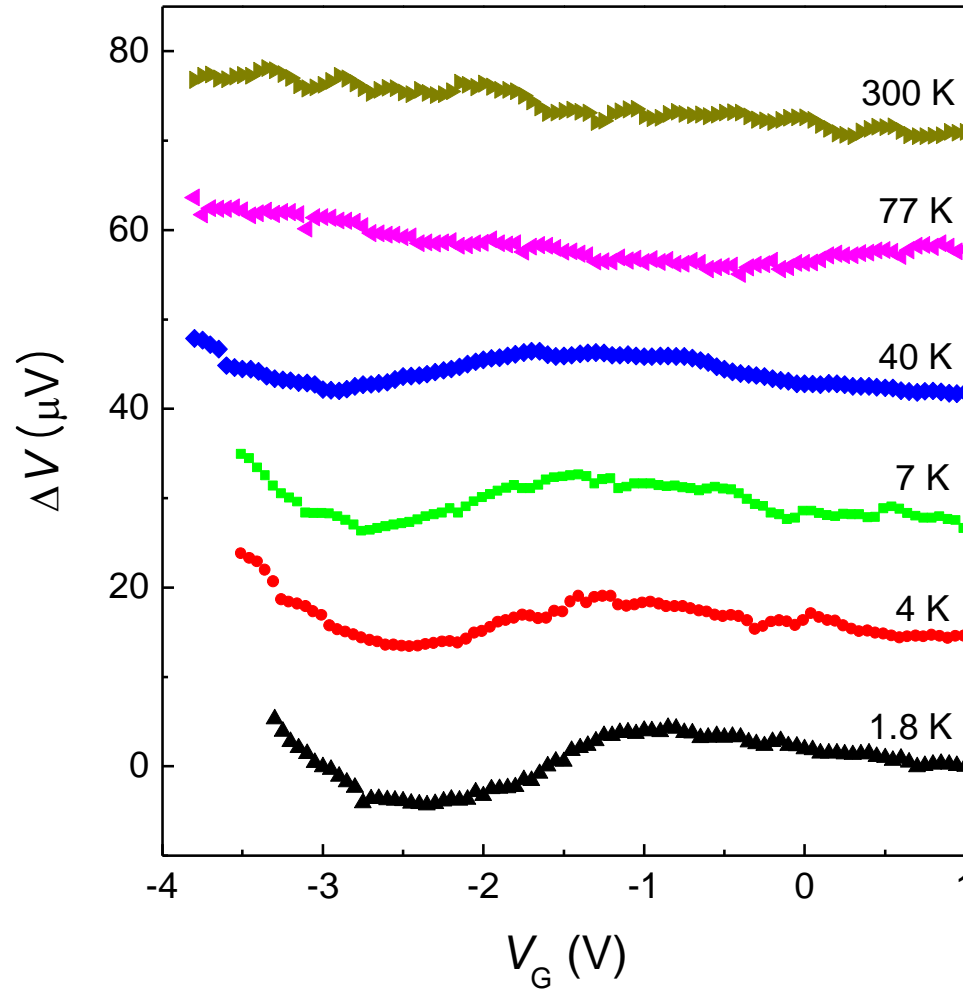
Fitting of Spin FET signals

H. C. Koo *et al.* *Science* 325,1515 (2009)

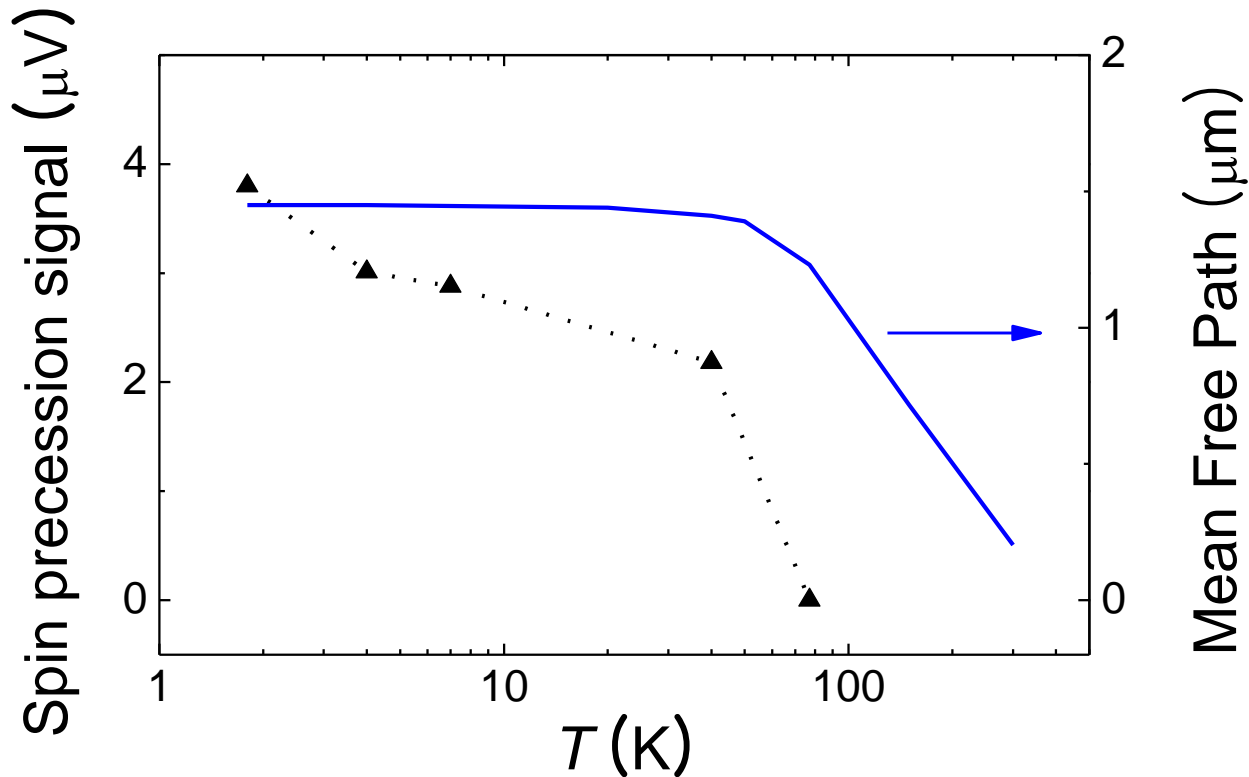
Period of oscillation signal when $L = 1.65 \mu\text{m}$: $\sim 2.5 \text{ V}$

when $L = 1.25 \mu\text{m}$: $\sim 3 \text{ V}$ ₃₁

Temperature dependence of spin precession signal

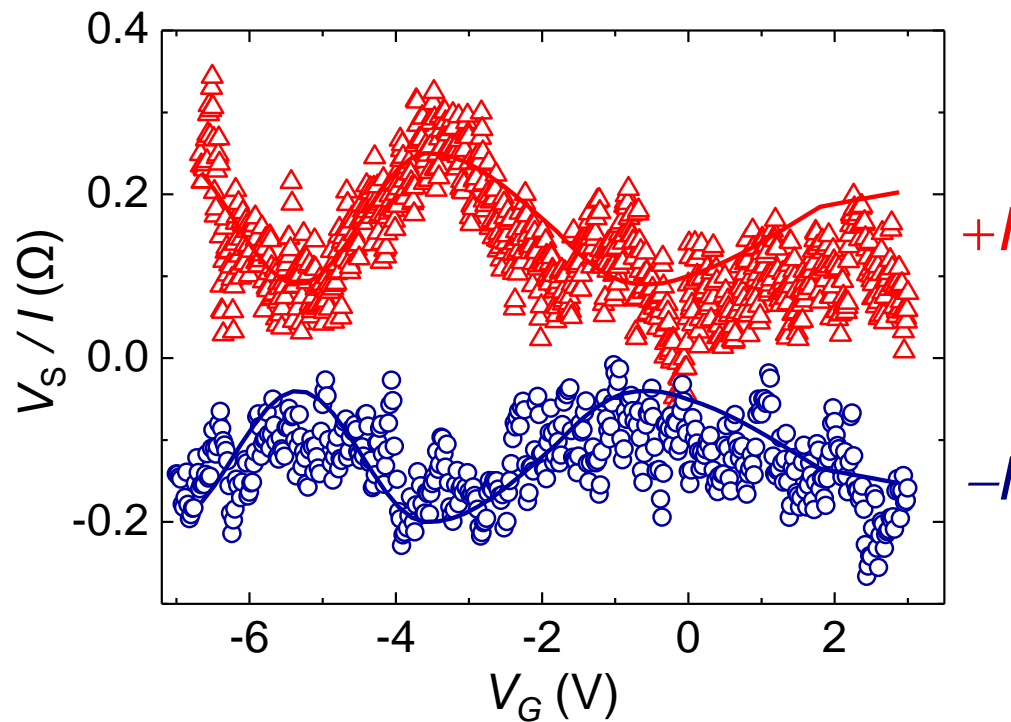
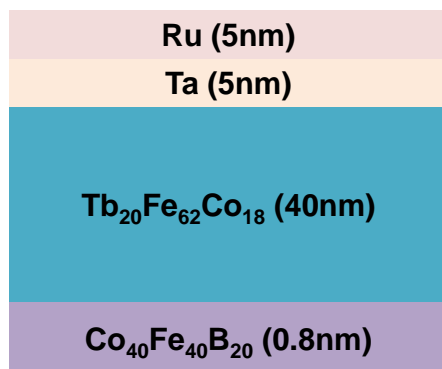


Spin precession signal and mean free path



H. C. Koo *et al.* *J. Phys. D: Appl. Phys.* (2011)

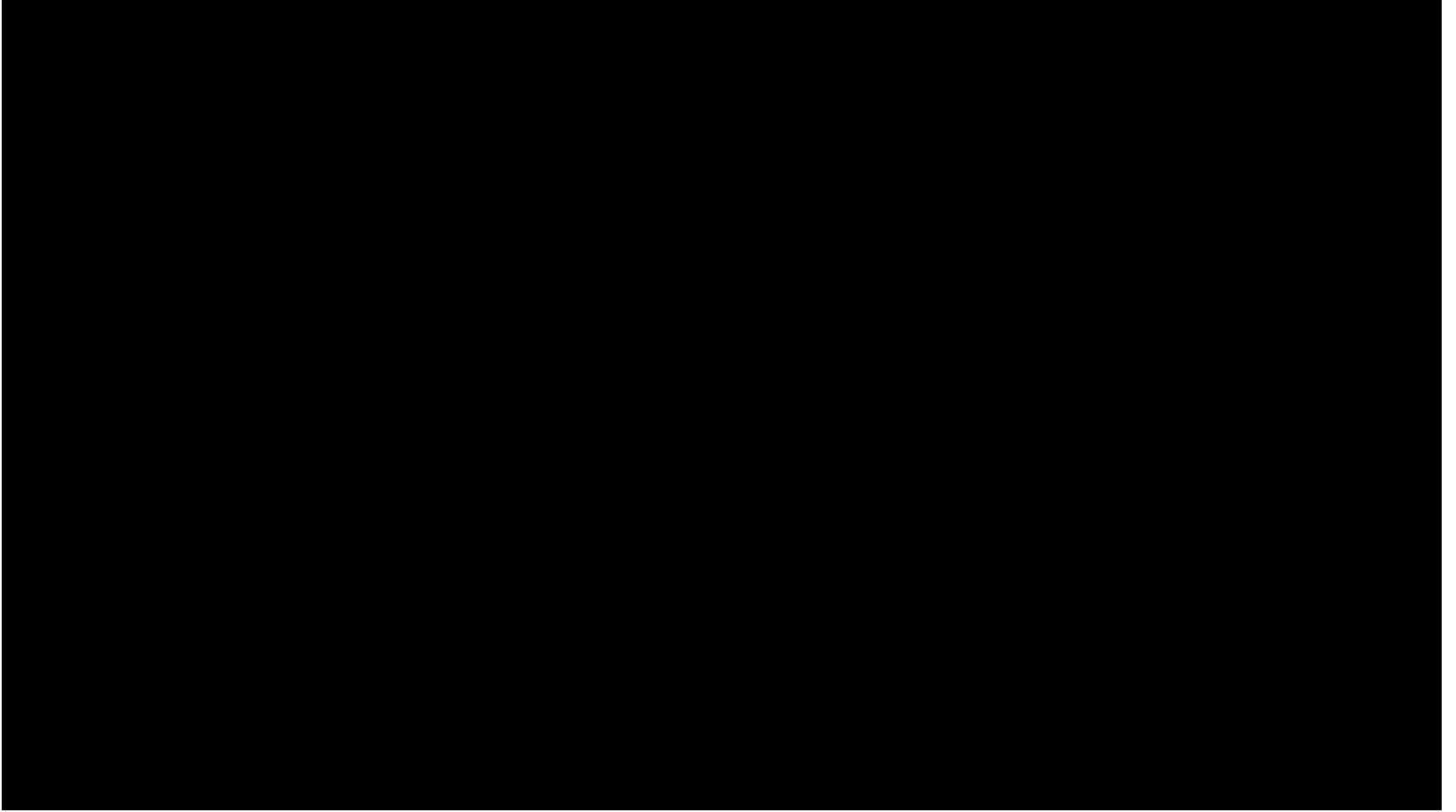
Spin precession signal with a perpendicular magnetization



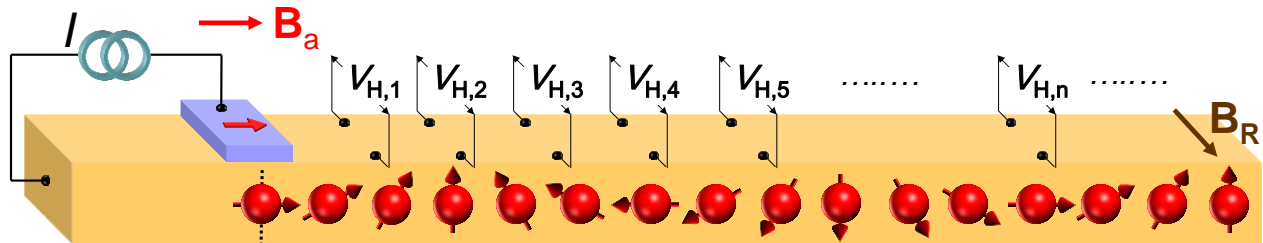
J. H. Kim *et al.* *J. of Magnetism and Magn. Mater.* (in press)

Spin Hall effect in a semiconductor channel

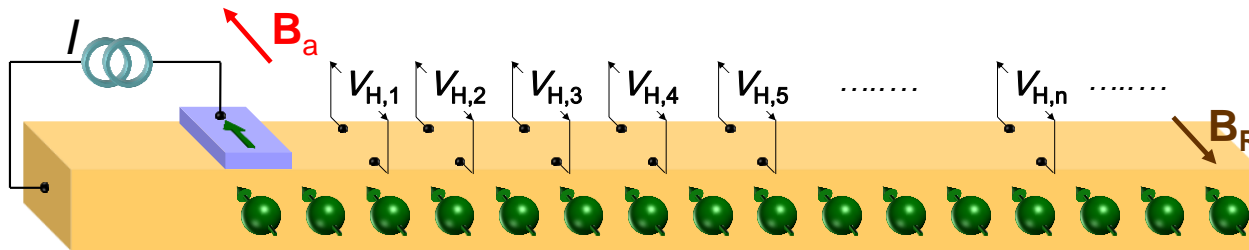
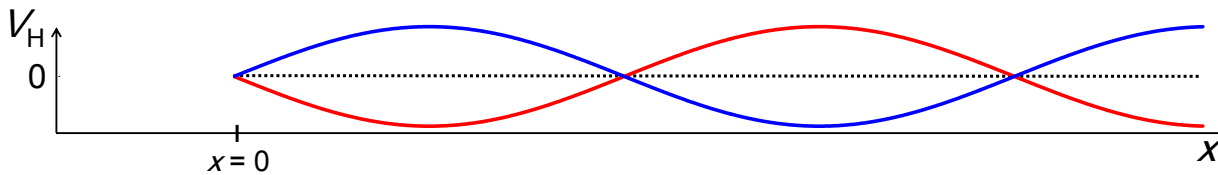
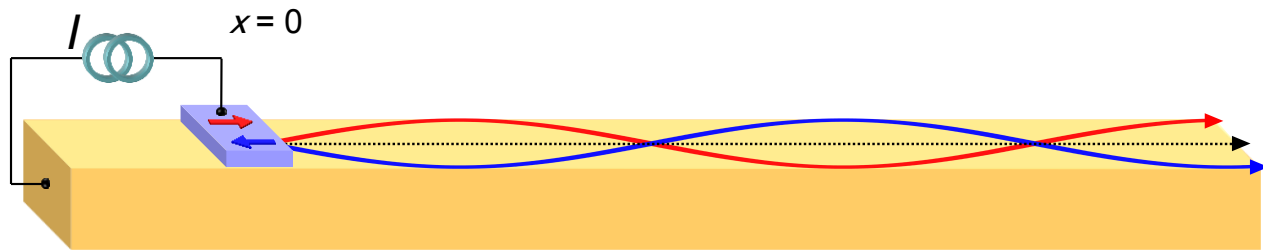
Spin Hall Transistor



Spin Hall effect and carrier movement



$B_a \perp B_R$:
Spin precession

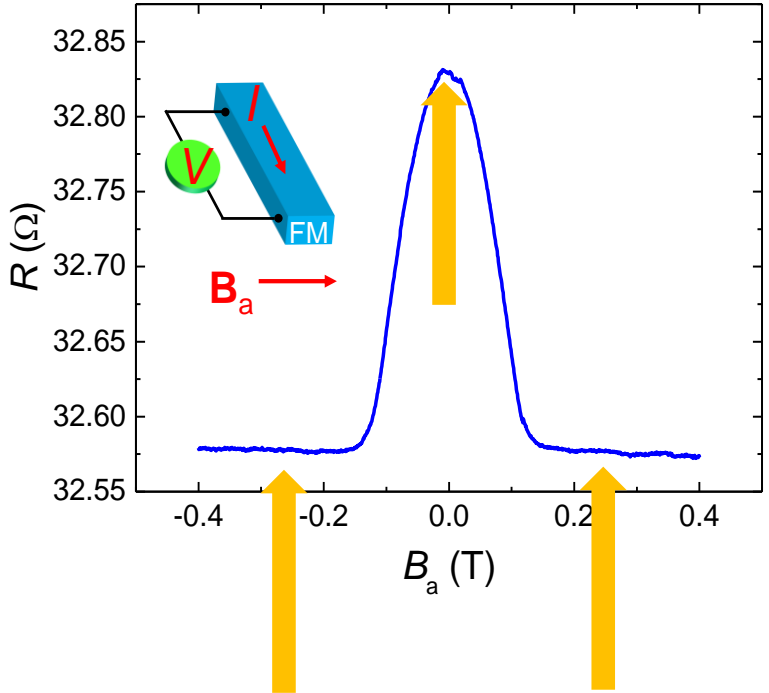


$B_a \parallel B_R$:
No Spin precession

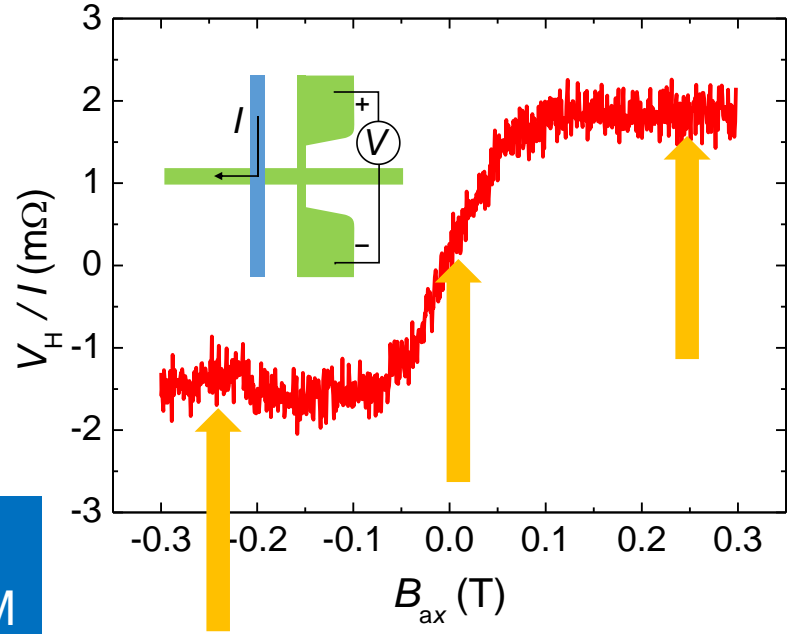
Spin Hall voltage as a function of Magnetization direction

Korea Institute of Science and Technology

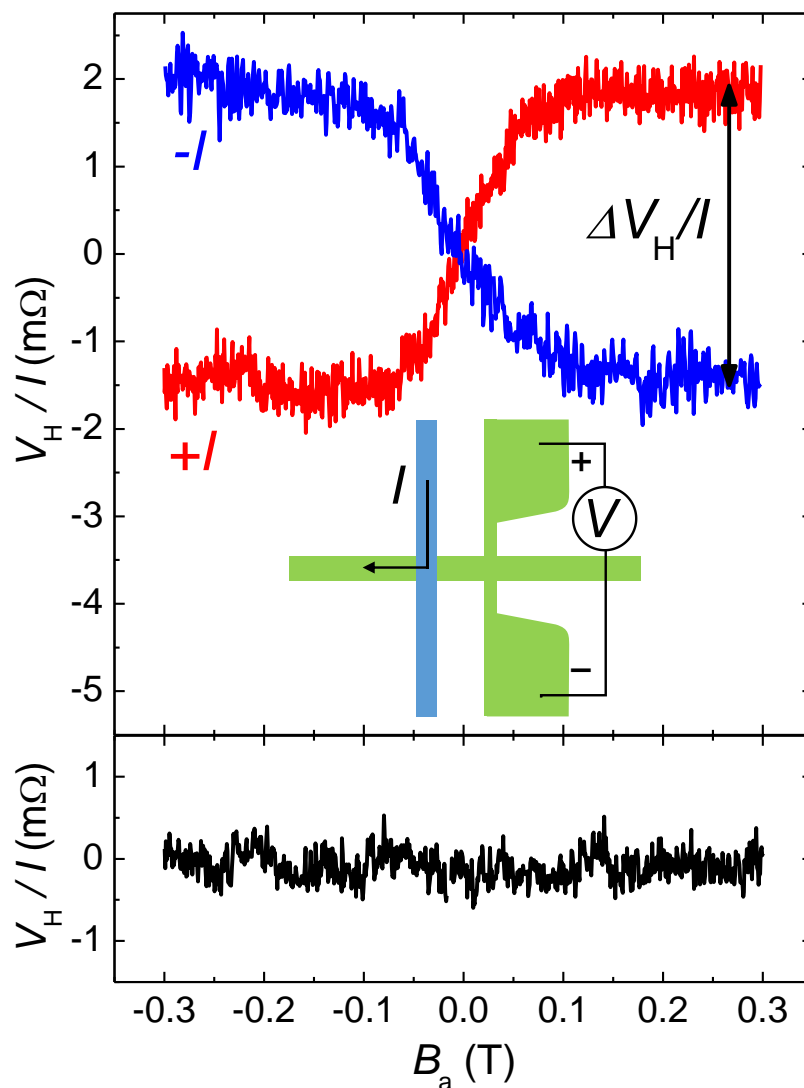
Anisotropic Magnetoresistance



Inverse spin Hall effect



Inverse spin Hall effect



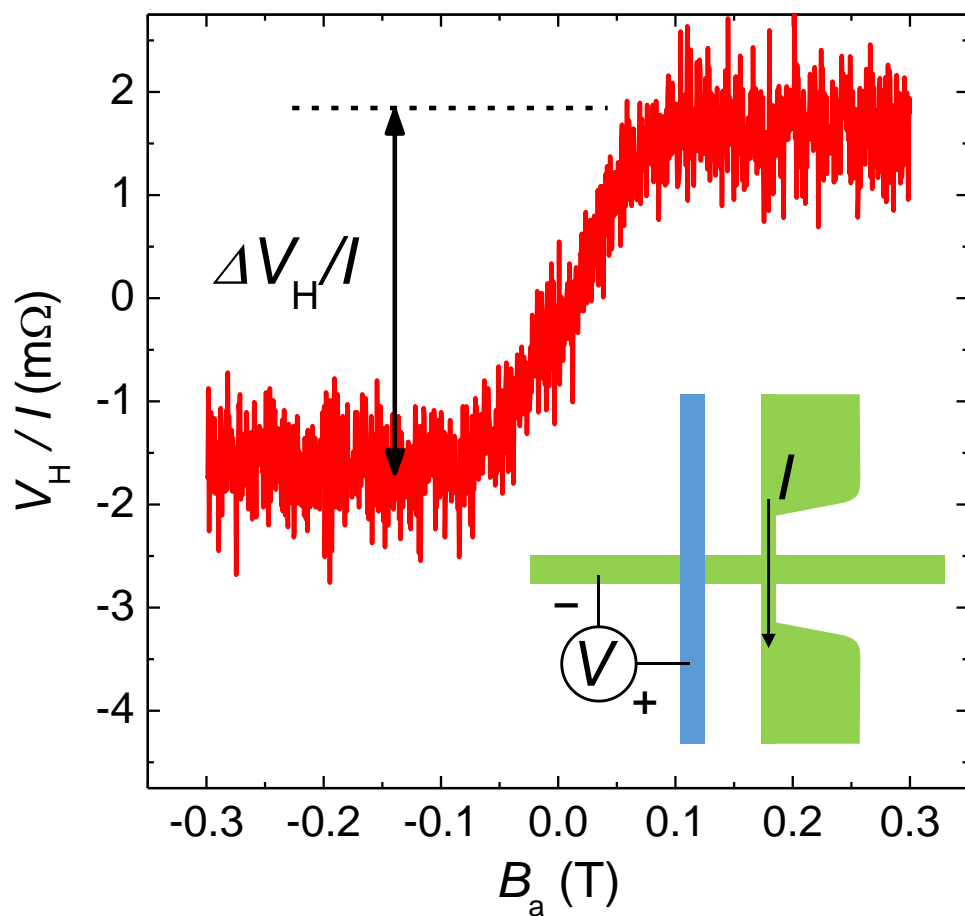
$B_a \perp B_R$:

- We observed **inverse spin Hall effect**.
- The sign of spin Hall voltage is determined by the sign of M and I .

$B_a \parallel B_R$:

No Spin precession

Direct spin Hall effect

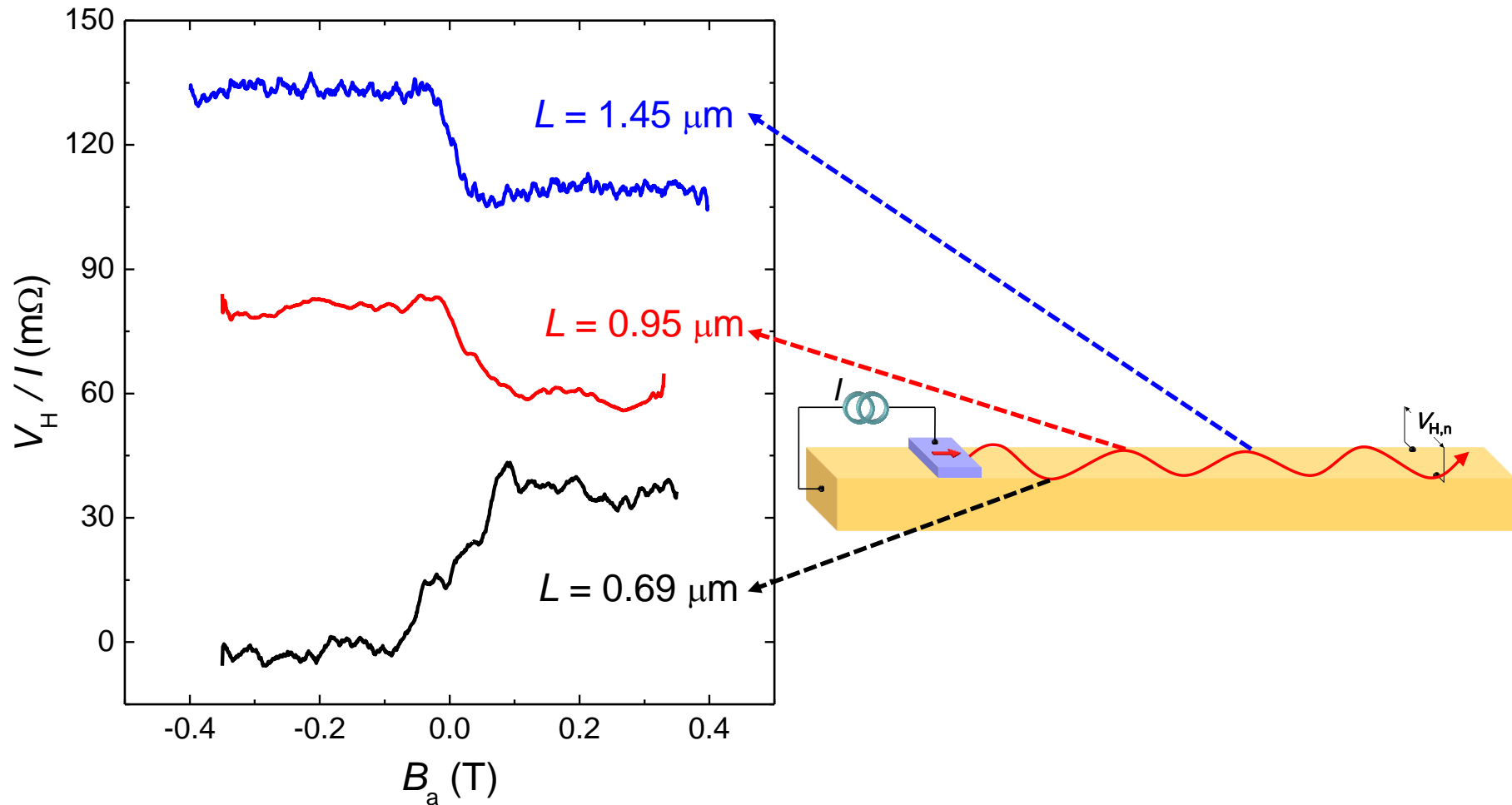


$B_a \perp B_R$:

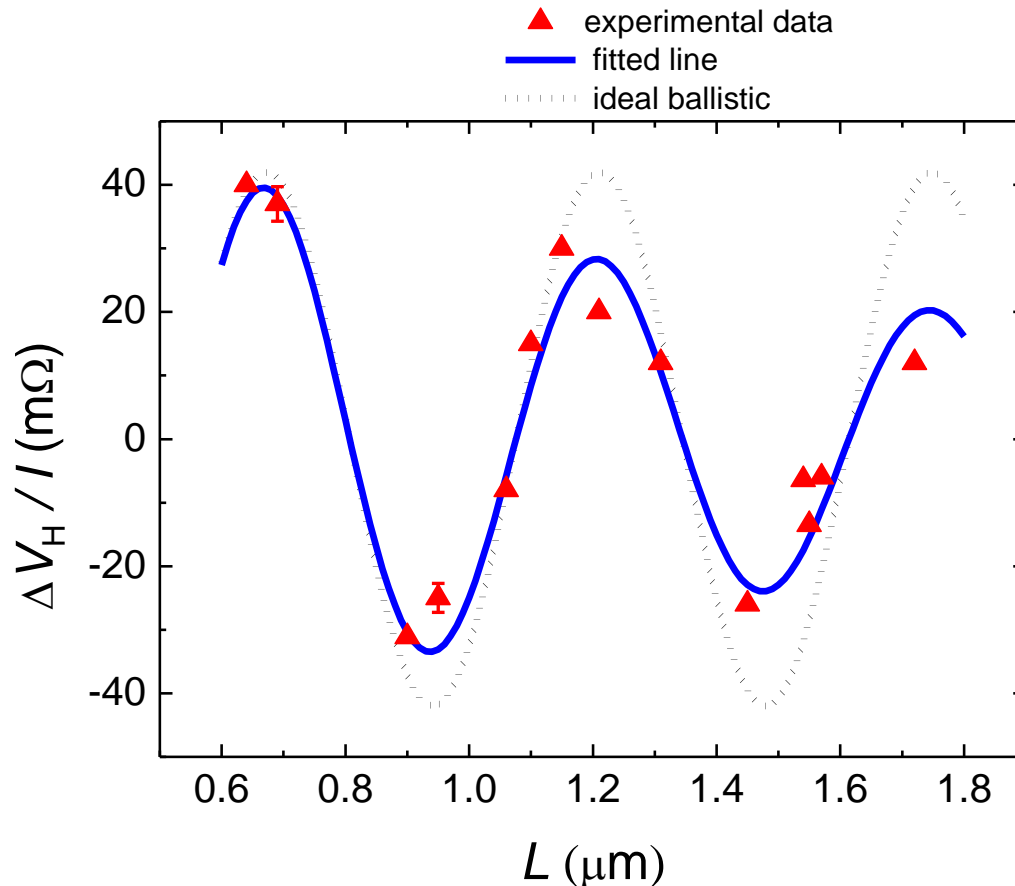
- We observed direct spin Hall effect.
- $\Delta V_{H,\text{direct}} = \Delta V_{H,\text{inverse}}$

W. Y. Choi *et al.* *Nature Nanotechnol.* 10, 666 (2015)

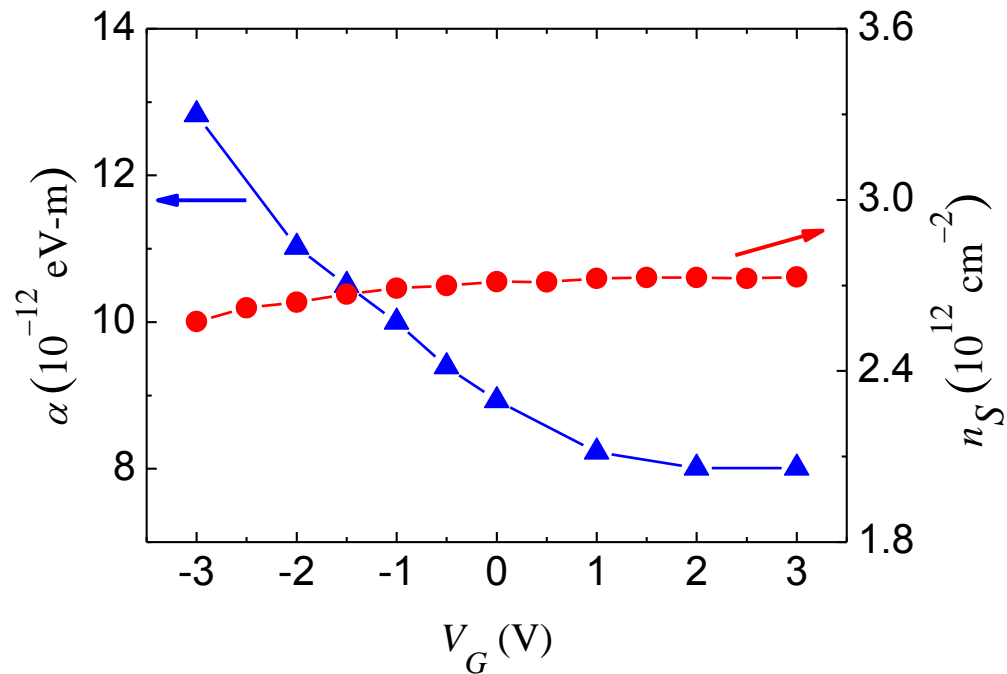
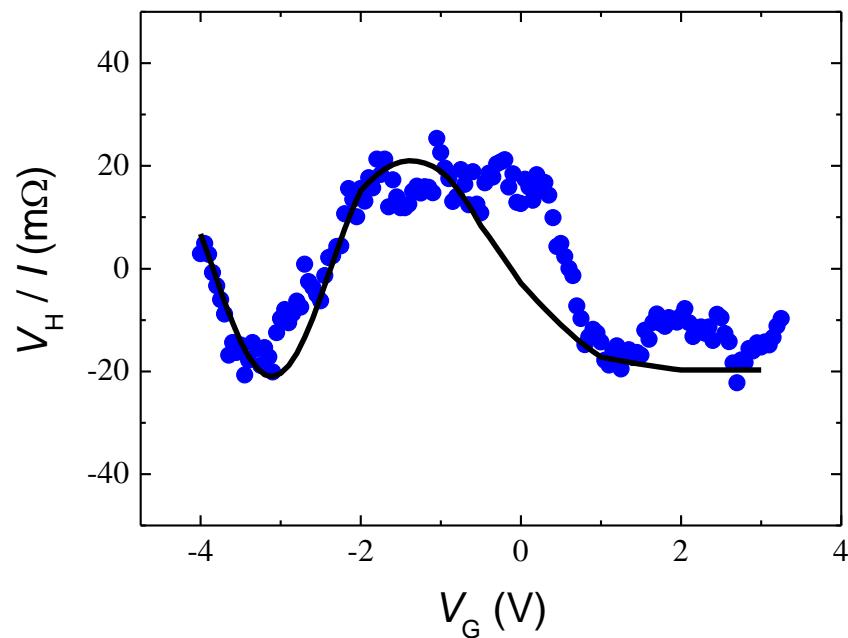
Spin Hall voltage for various lengths



Ballistic spin Hall effect



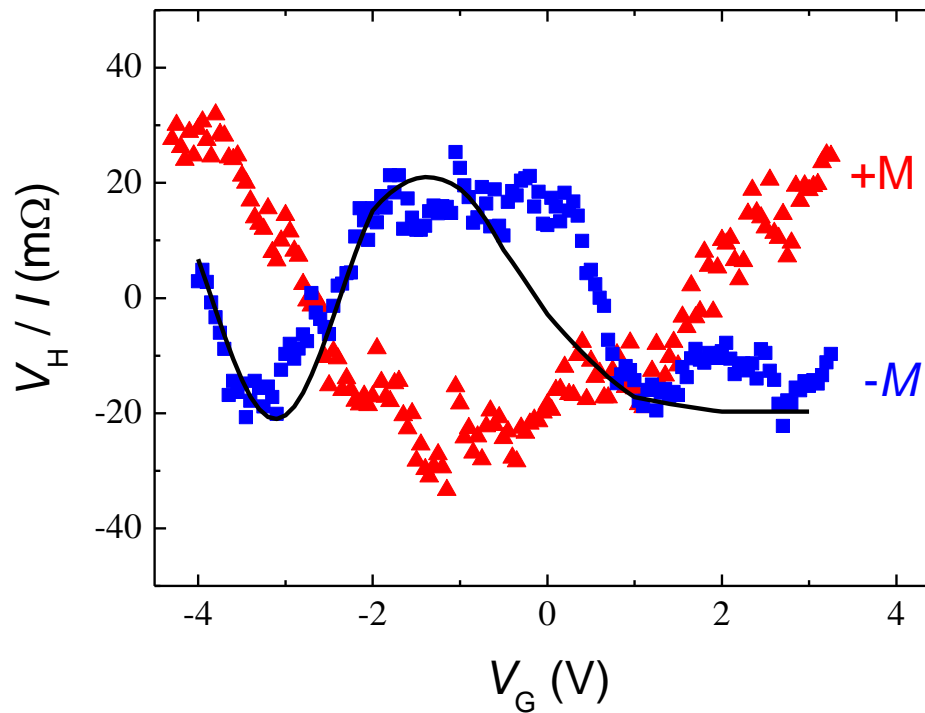
- The Datta–Das conductance oscillation are clearly seen.
- The solid line fit includes an exponential decay $e^{-L/l}$ governed by the mean free path of ballistic trajectories. ($l = 1.61 \mu m$)



W. Y. Choi *et al.* *Nature Nanotechnol.* 10, 666 (2015)

- Gate controlled spin Hall signal is nicely matched with gate dependence of Rashba parameter.

Gate control: application to complementary device



- When the M is reversed, the injected electrons have spins with opposite orientation and the sinusoidal trajectories are shifted in phase by 180° .
→ Complementary logic is possible.

Summary

- All electric spin injection was achieved in an InAs quantum well layer.
- We determined the absolute values of the Rashba and Dresselhaus parameters separately.
- Spin-FET signal was detected in the quasi-ballistic regime.
- Ballistic spin Hall voltage in a semiconductor channel was observed using direct and inverse spin Hall effect.
- Spin Hall signal was modulated by the gate voltage.

Future direction

: Total Solution of Mobile Electronics

